

GEM Detectors for COMPASS

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Solid State Detectors Seminar

Outline

- The COMPASS experiment
- Gas Electron Multiplier basics
- Discharge studies
- Design of COMPASS GEM detectors
- Construction
- Quality control
- Readout electronics
- Performance in the beam
- Summary and Outlook



COMPASS GEM

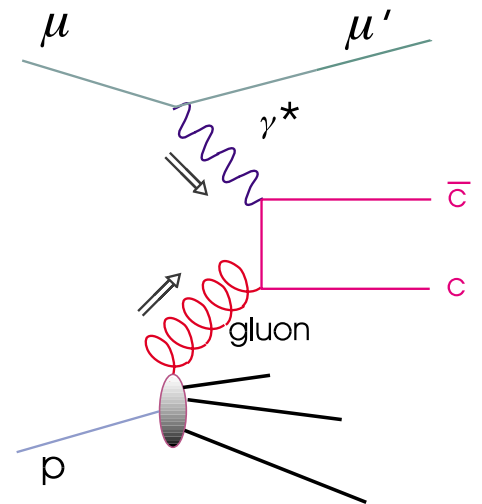
The Physics Program

COmmon MUon and P roton Apparatus for S tructure and S pectroscopy

Muon beam

- Gluon polarization $\Delta G/G$

Photon-gluon fusion

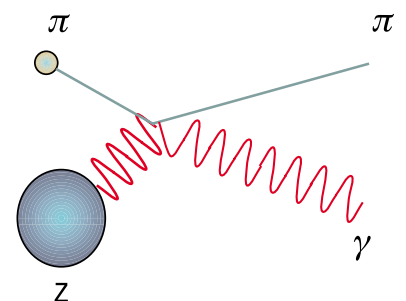


- Longitudinal and transversal spin distribution
- Polarization of Λ and $\bar{\Lambda}$

Hadron beam

- Study of charm hadrons
- Study of hadron structure with virtual photons

Primakoff scattering

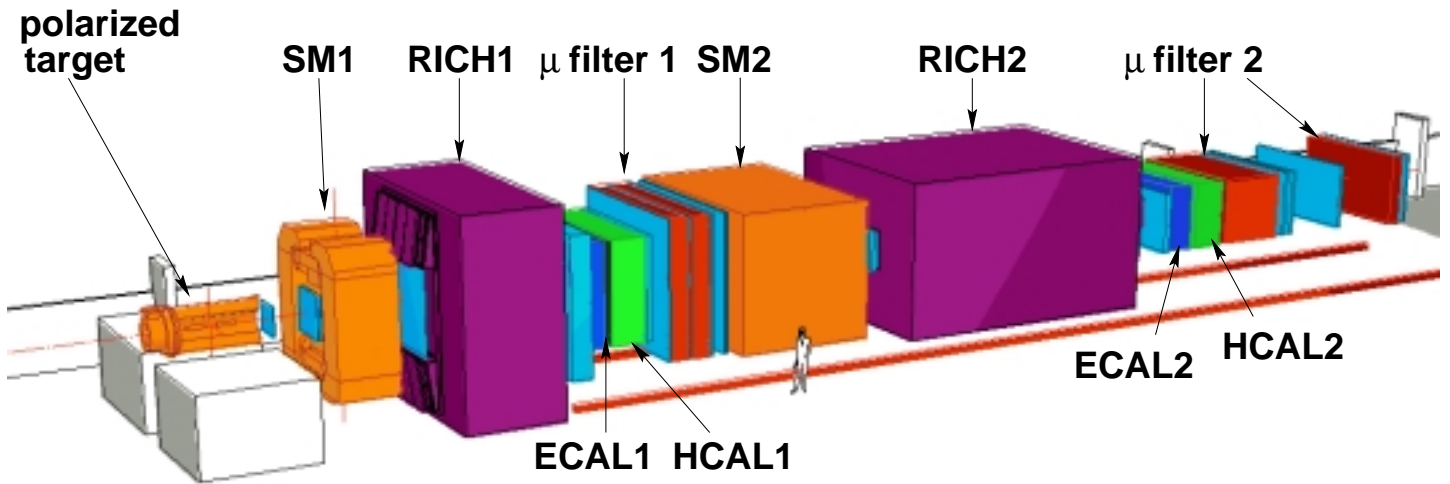


- Exotic hadrons (glueballs, hybrids)



The Spectrometer

Fixed target experiment at the SPS of CERN



■ Magnets
 ■ Tracking
 ■ RICH
 ■ ECAL
 ■ HCAL
 ■ μ filter

Target:	Polarized ${}^6\text{LiD}$, liquid hydrogen, active charm target	
Tracking: before SM1 after SM1	large area	small area
	Drift chambers Straws, MWPC	Micromegas, Si, SciFi GEM, Si, SciFi
Particle Id:	2 RICH with MWPC + CsI photocathode pads	
	RICH 1 RICH 2	C_4F_{10} $\text{C}_2\text{F}_6 + \text{Ne}$
Calorimetry:	electromagnetic, hadronic	
	ECAL HCAL	lead glass + PbWO_4 lead/scintillator
Muon Id: after walls after 2nd wall	Muon filter walls	concrete + iron
	Drift tubes (ϕ 3 cm)	
	Scintillator hodoscopes	



COMPASS GEM

Bernhard Ketzer



Tracking

Beam parameters	Muon beam μ^+, μ^-	Hadron beam p, K, π
$x \times y$ (RMS) (mm ²)	7.8×7.8	1.5×1.1
$x' \times y'$ (RMS) (mrad)	0.4×0.8	0.29×0.48
Momentum (GeV/c)	100–200	270–300
Flux (per spill)	1.8×10^8	10^8

Trigger rates

Muon program 10 kHz

Hadron program 10 – 100 kHz

Requirements for Small Area Trackers

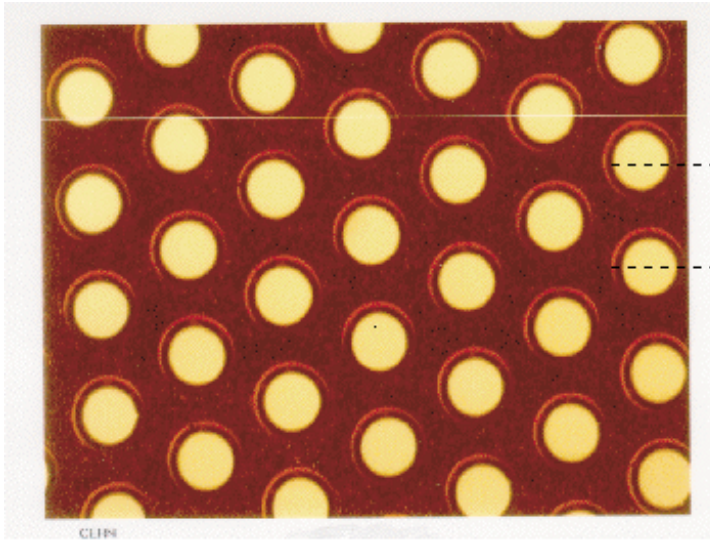
- High rate capability
- High spatial resolution
- Large active area
- "Massless detectors"

⇒ Micropattern gas detectors

Micromegas 12 muon program
GEM 20 hadron + muon program



GEM – Principle

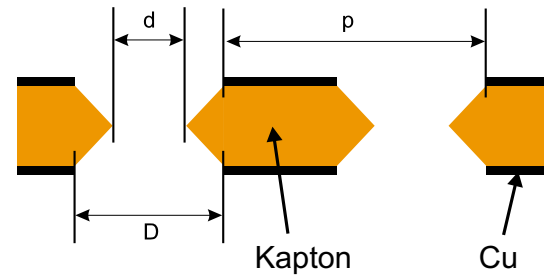


Typical dimensions:

$$D = 70 \mu\text{m}$$

$$d = 60 \mu\text{m}$$

$$p = 140 \mu\text{m}$$

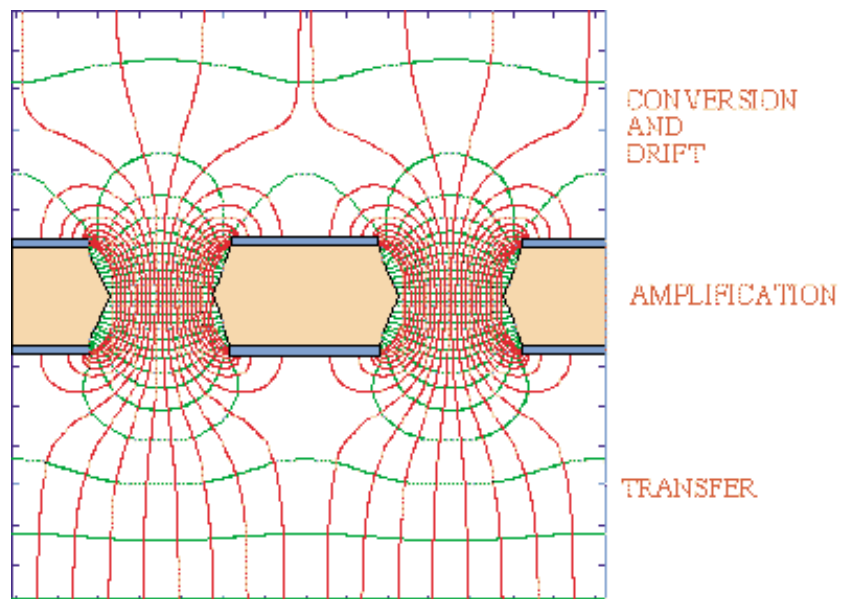


Gas Electron Multiplier [F. Sauli, NIM A386, 531 (1997)]

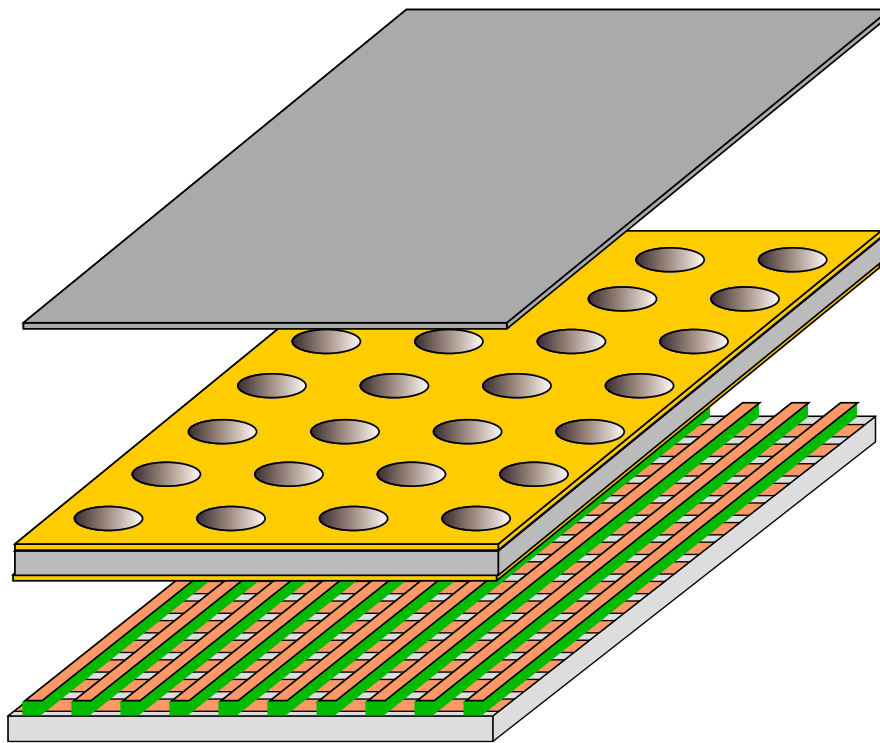
- Thin polymer (Kapton) foil, typ. $50 \mu\text{m}$ thick
- Metal-clad on both sides, typ. $5 \mu\text{m}$ Cu
- Perforated by large number of holes, typ. $10000/\text{cm}^2$: photolithography + etching process

- $\Delta U \sim 500 \text{ V}$ between electrodes \Rightarrow high electric field inside holes:

Proportional avalanche multiplication



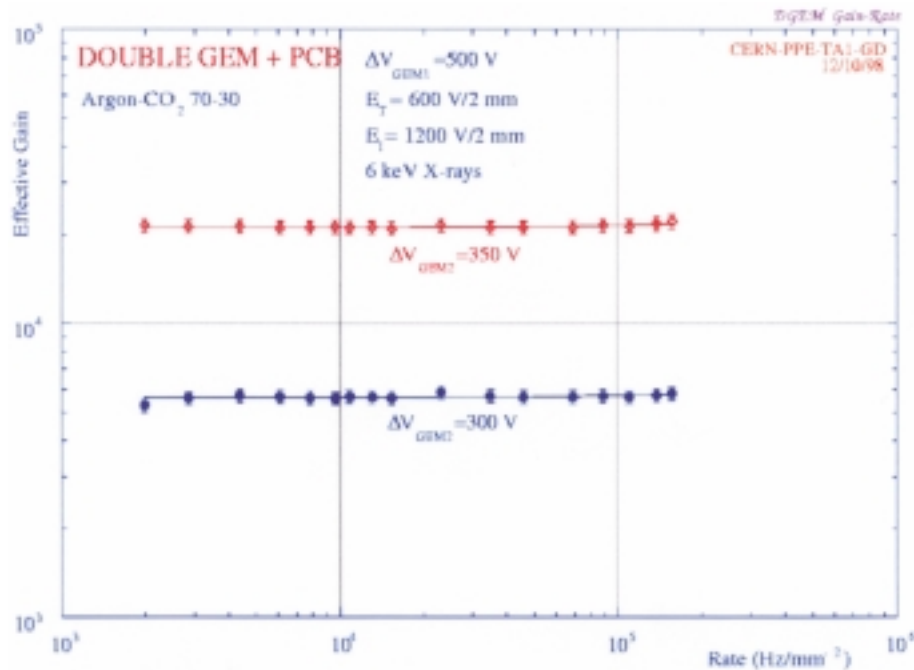
GEM-based Detector



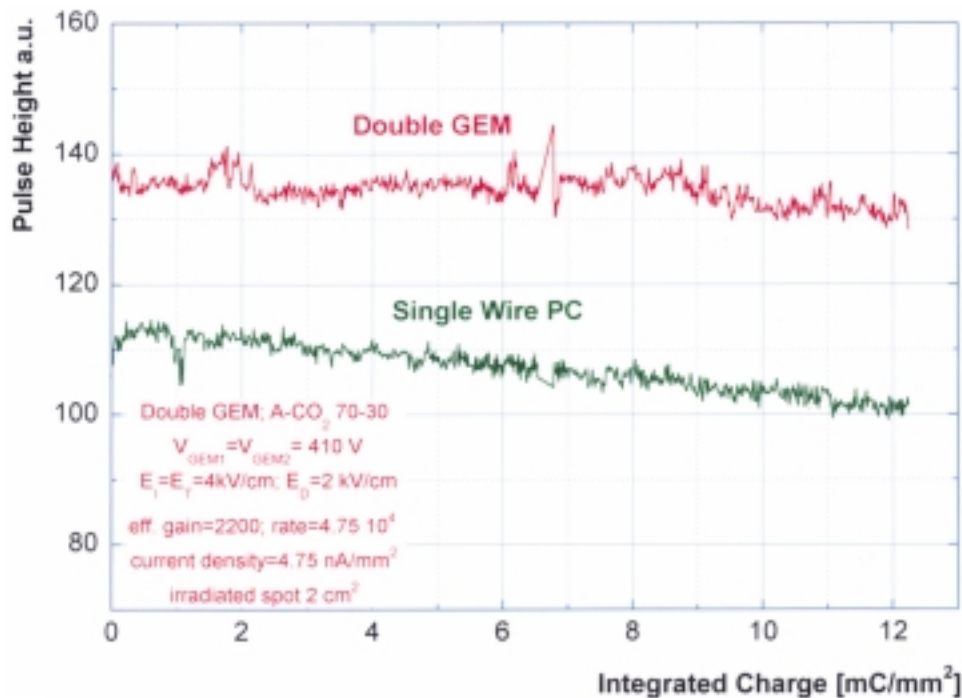
- Gain is a property of GEM foil
⇒ little dependence on external fields (mechanical tolerances!)
- Signal on readout electrode entirely due to electron collection
- No slow ion tail, no ion feedback
- Possibility to cascade several GEM foils ⇒ higher gain
- Separation of gas amplification and readout stage
⇒ high flexibility!
- Readout electrodes remain on ground potential

GEM Detectors - Properties

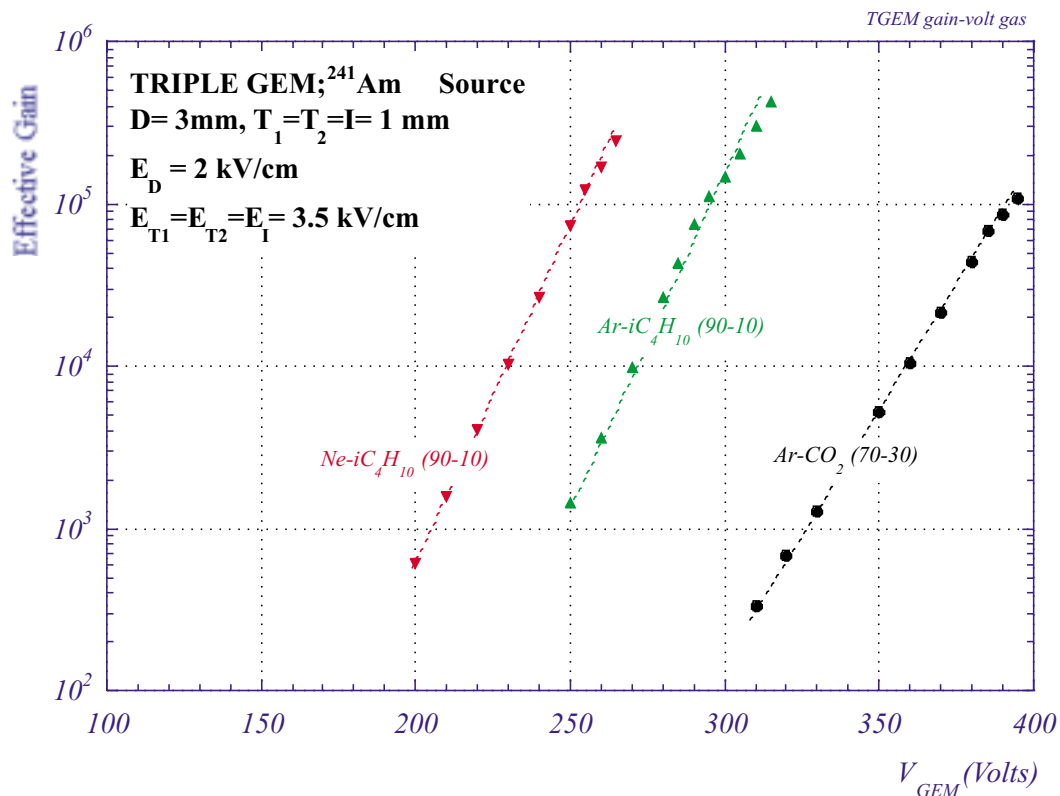
High rate capability $> 10^5 \text{ Hz/mm}^2$



No aging observed up to 10 mC/mm^2



Choice of Gas Filling



Requirements for use in high rate HEP applications:

- Non-polymerizing (aging!)
- Large drift velocity
- Low diffusion
- High gain at low operating voltages
- Non-flammable

⇒ Ar/CO_2 (70%/30%)



Gas Discharges



- Due to manufacturing defects \Rightarrow QC
- Due to nuclear interactions on exposure to heavily ionizing tracks

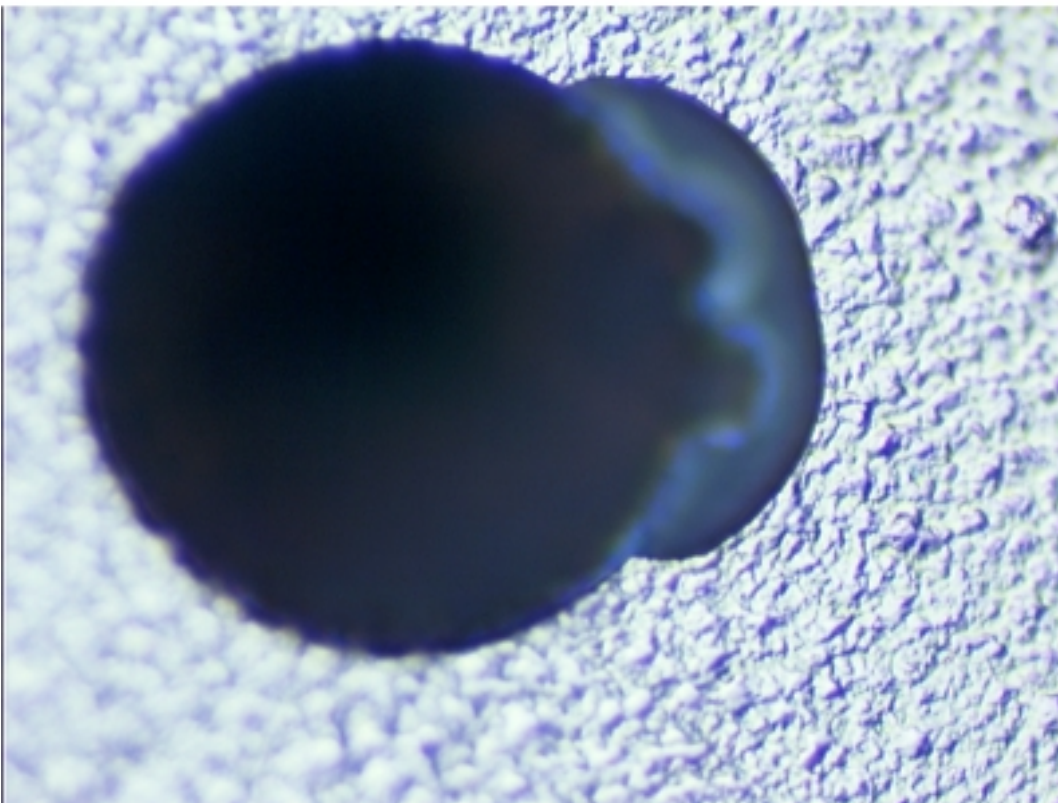
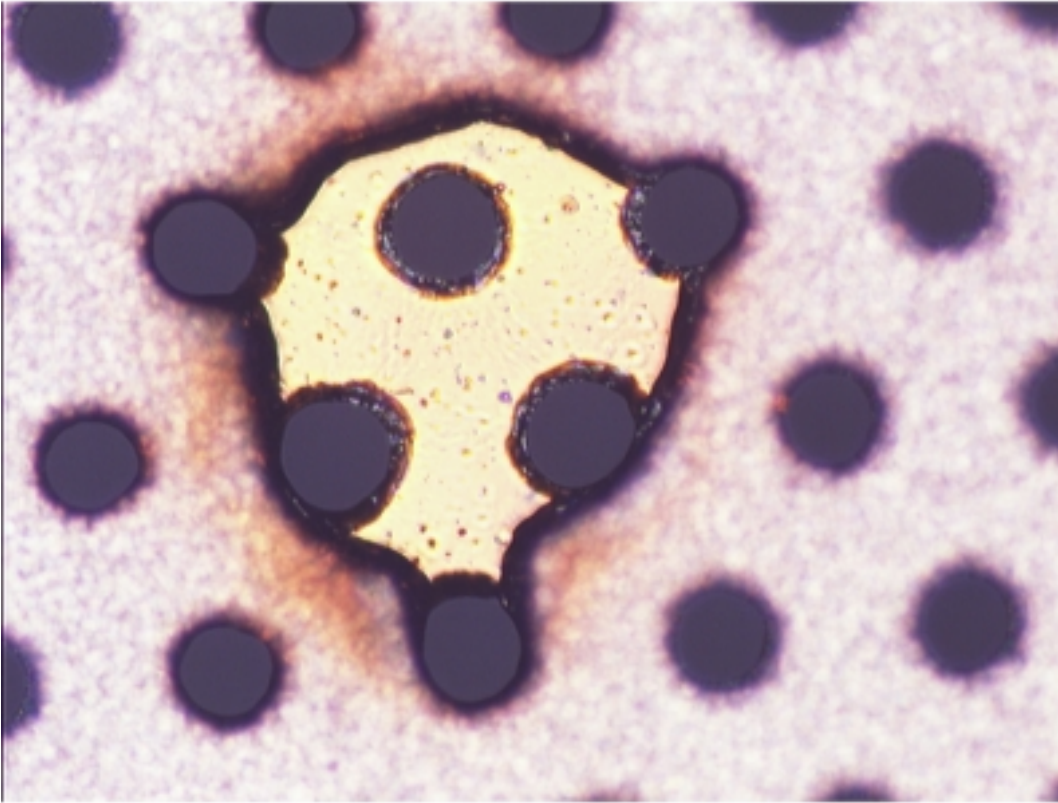
Systematic investigation of

- Probability of discharge
- Energy/charge released in a discharge

\Rightarrow Strategies to optimize GEM detectors for successful operation under harsh COMPASS conditions

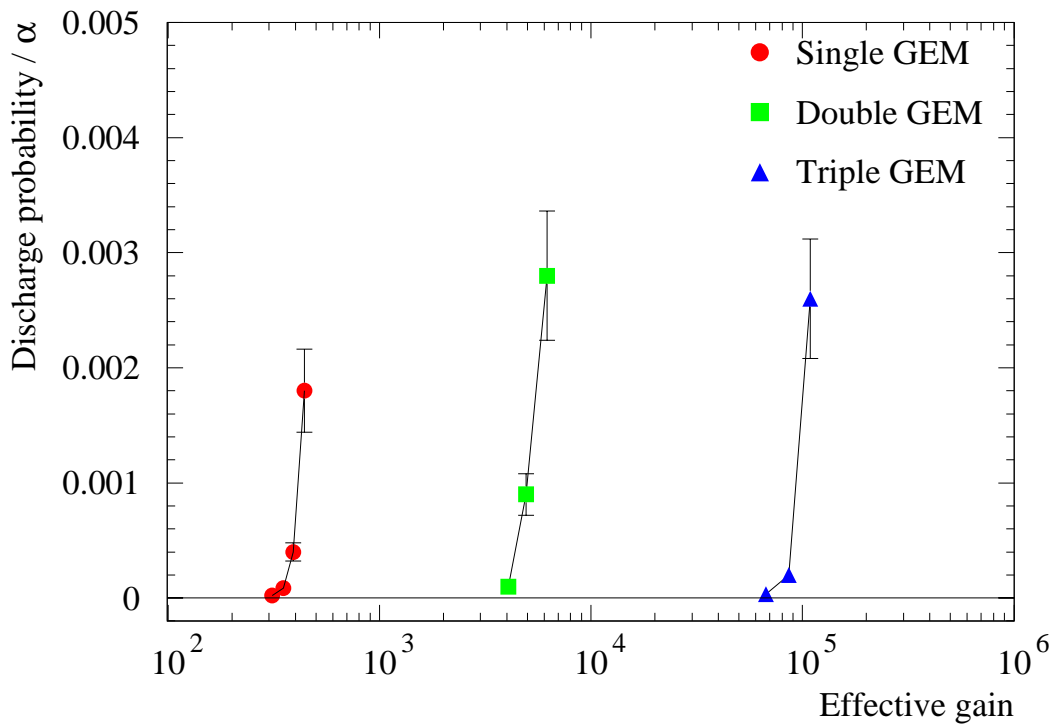
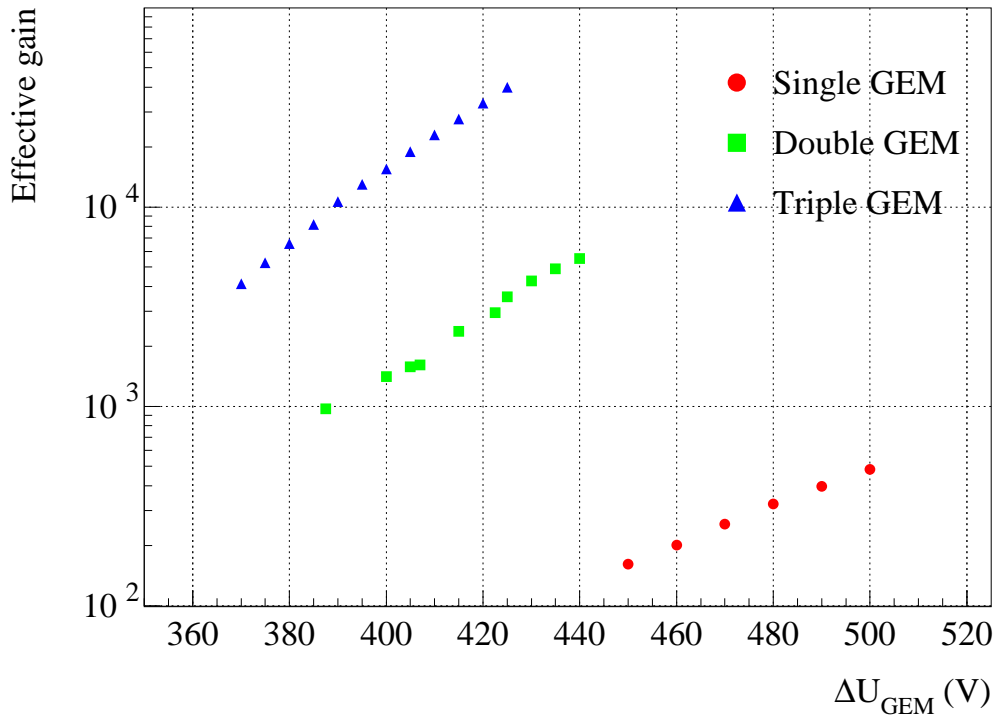


Defects in GEM Foils



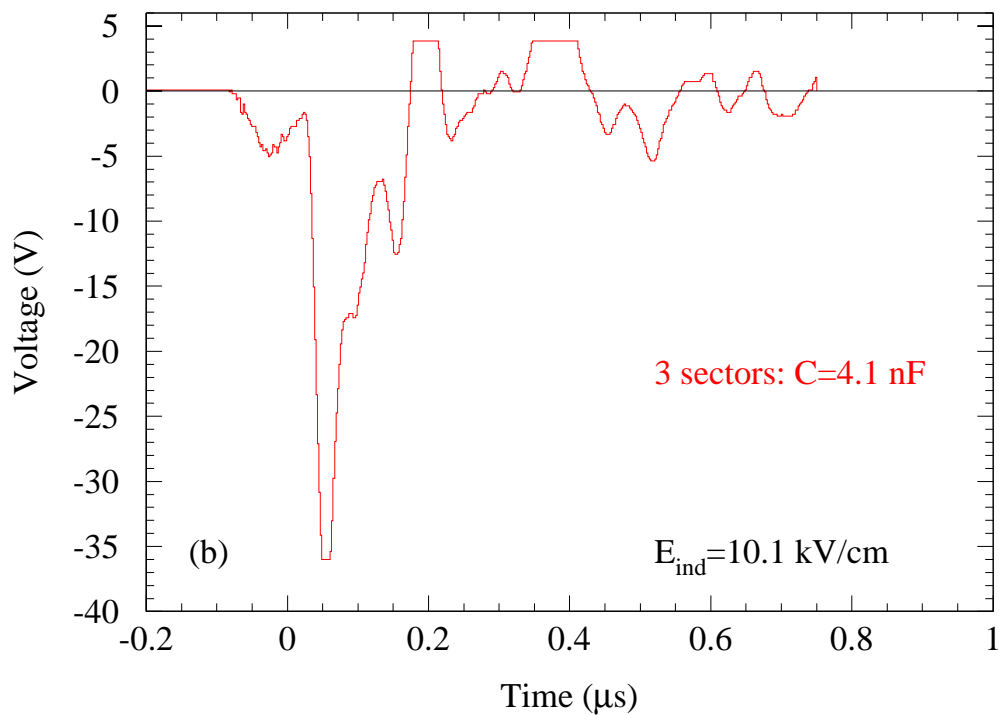
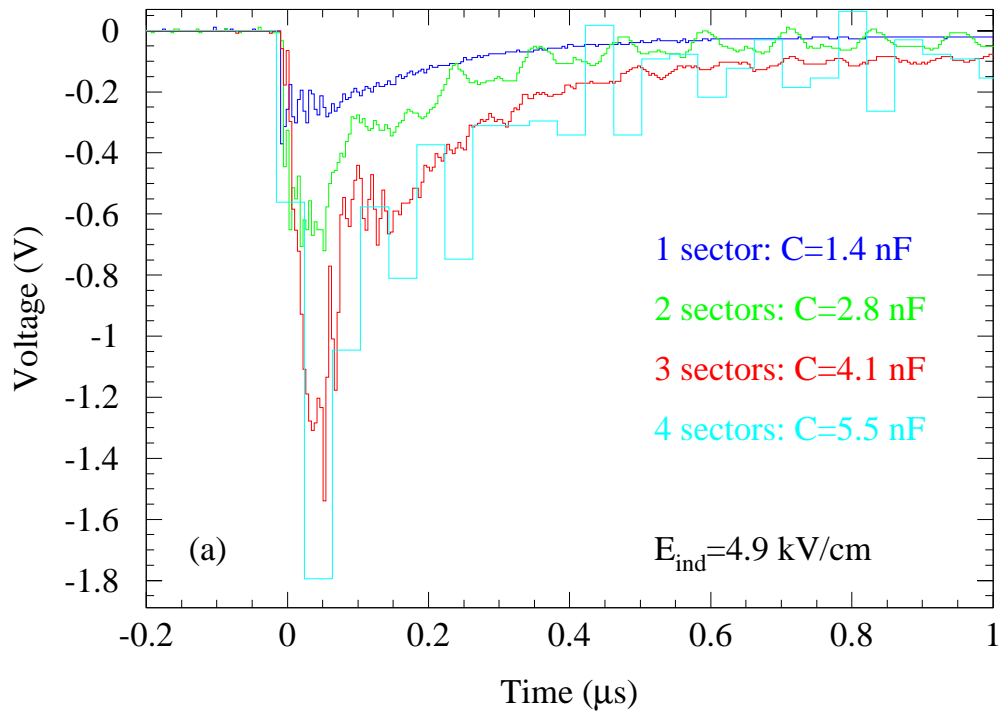
Discharge Probability

$10 \times 10 \text{ cm}^2$ GEM, 5.5 MeV α (^{241}Am)

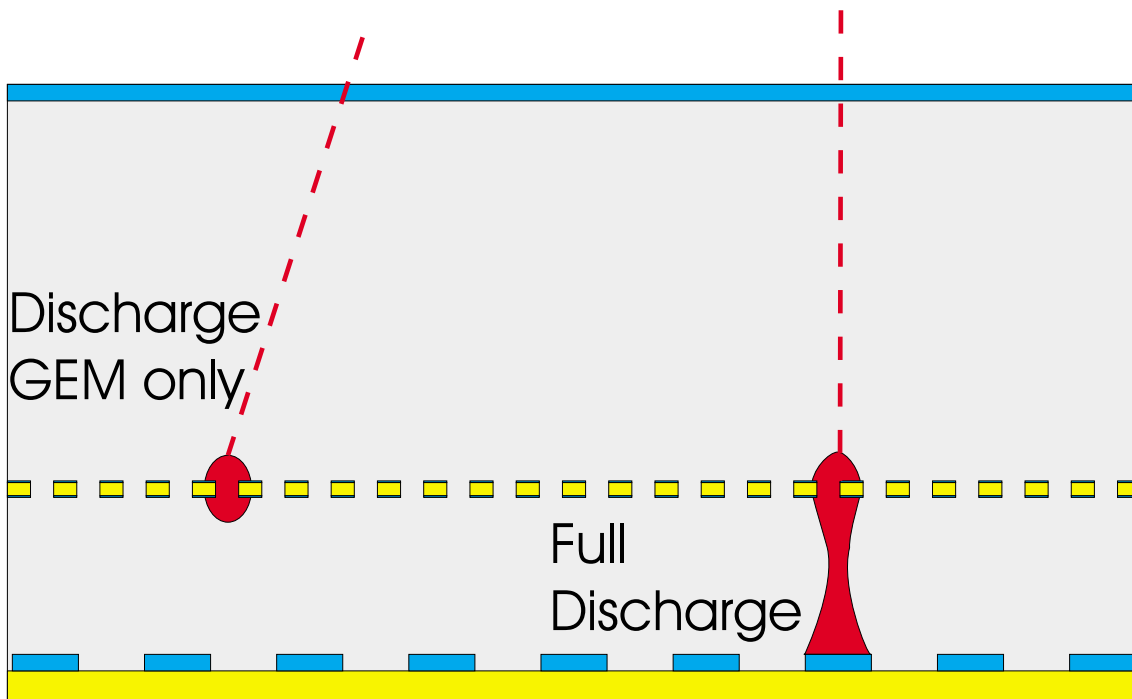


Discharge Energy I

$10 \times 10 \text{ cm}^2$ DGEM, sectorized, 5.3 – 8.8 MeV α (^{228}Th)



Discharge Energy II



Discharges in GEM only

- Charge released depends on capacitance between electrodes
- Fraction of charge collected depends on induction field
- Duration ~ 200 ns $\Rightarrow Q \sim 2.5 - 10$ nC

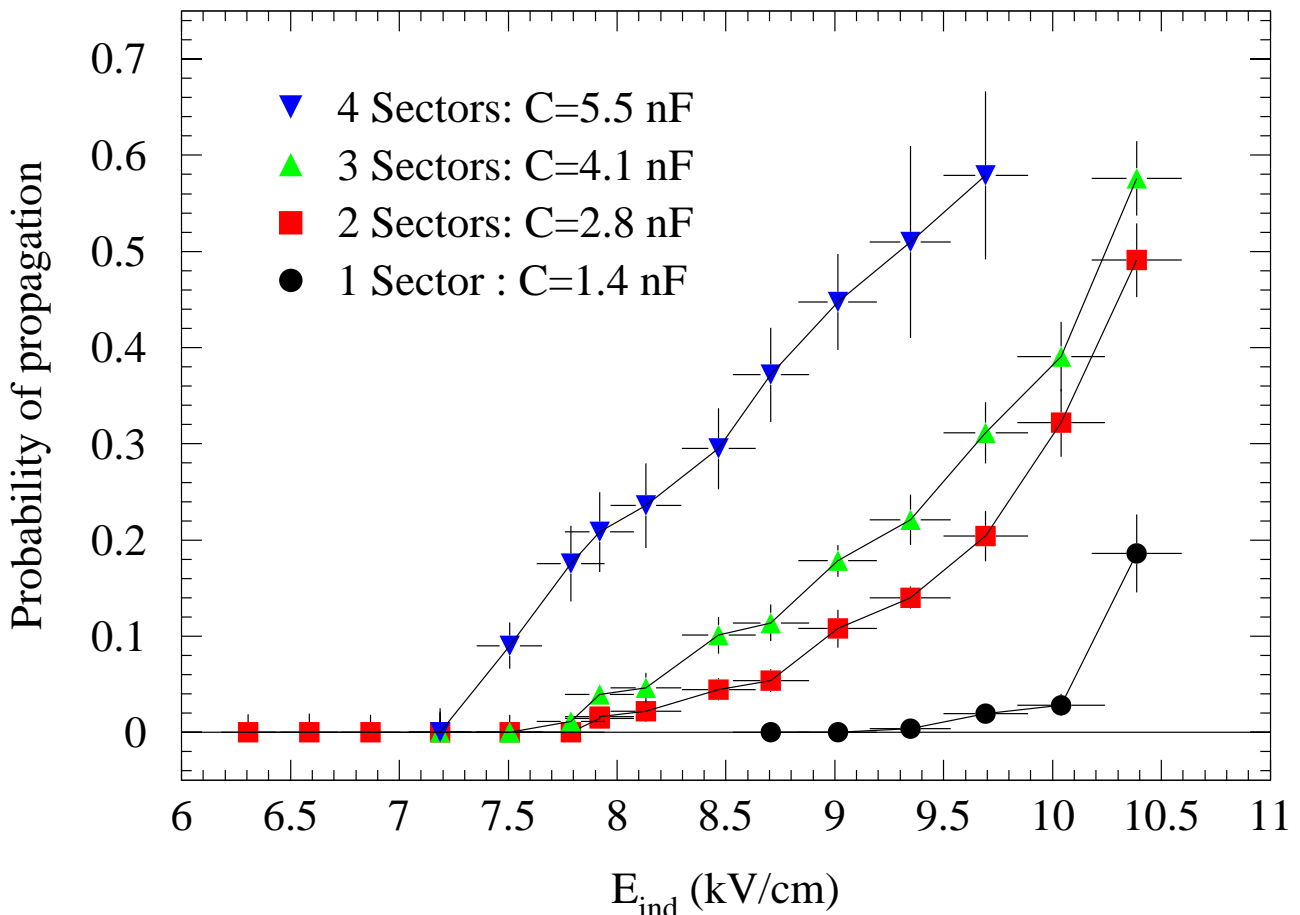
Full discharges to readout strips

- Charge released determined by capacitance and potential difference between readout and lower GEM electrode ($C \sim 60$ pF for 10×10 cm² GEM; $\Delta U \sim 800 - 2000$ V)
- Charge $Q \sim 50 - 120$ nC, current $I \sim 1$ A

\Rightarrow Protection of FE chip necessary!

Probability of Full Discharges

$10 \times 10 \text{ cm}^2$ DGEM, sectorized, 5.3 – 8.8 MeV α (^{228}Th)



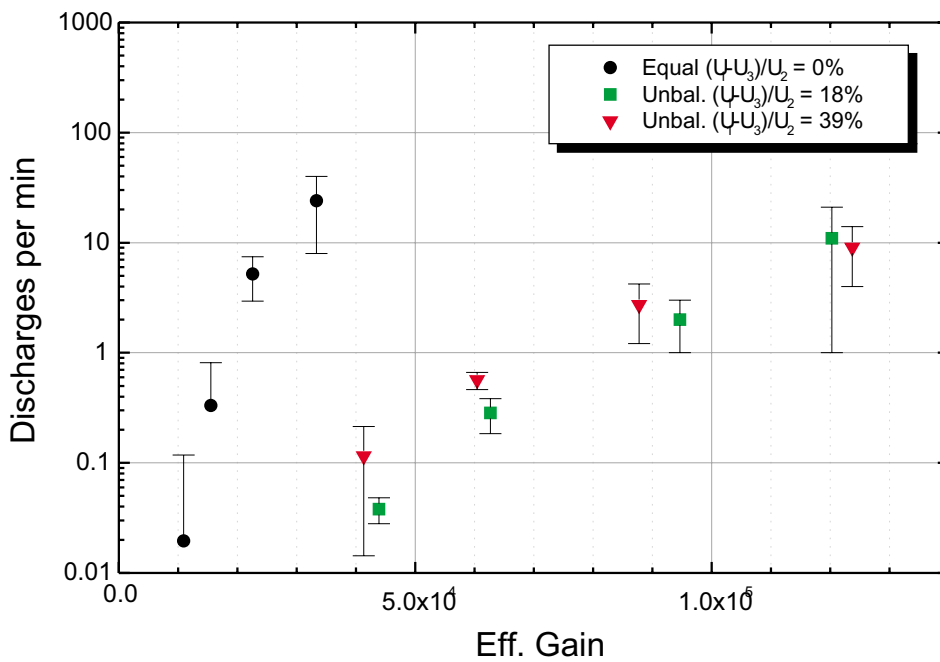
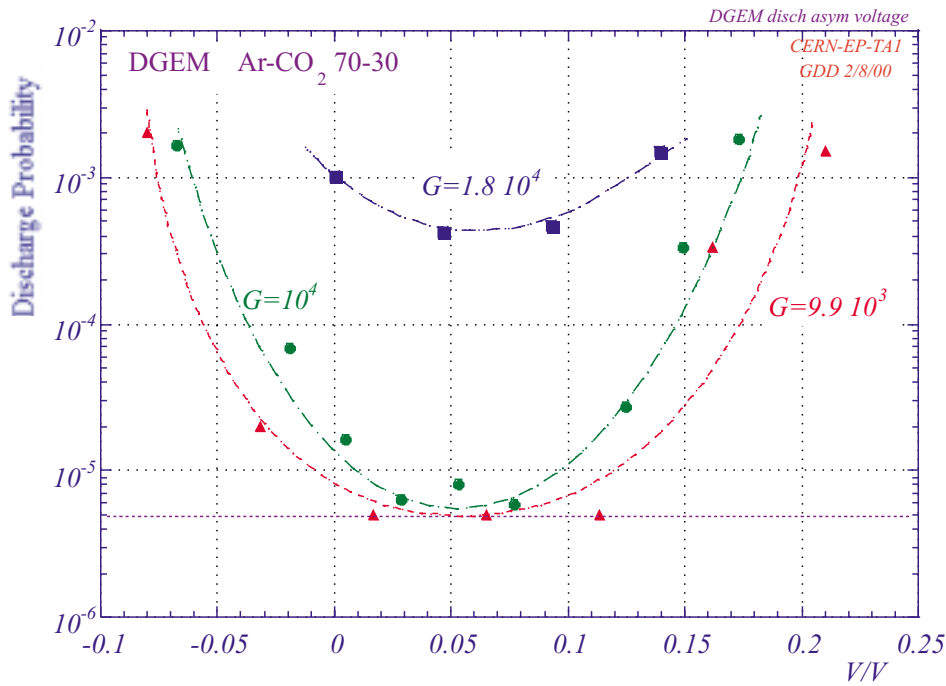
- Probability of propagation depends on E_{ind} and energy of primary discharge (GEM capacitance)

⇒ Can be decreased by decreasing sector size:

13 sectors instead of 5



Sharing of Gain

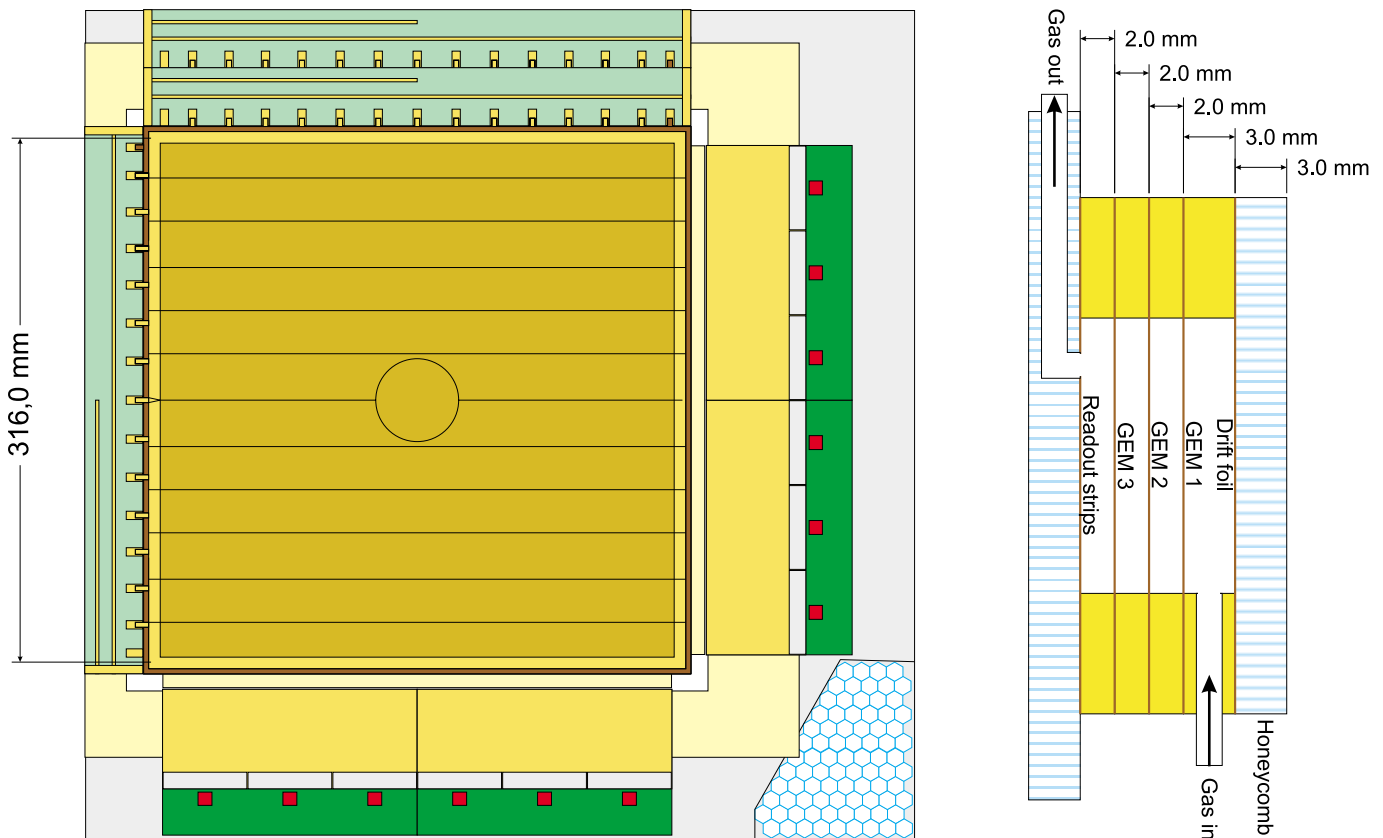


Asymmetric gain sharing between GEMs

⇒ probability of discharges lower by 2 orders of magnitude at given gain



COMPASS GEM design I



Triple GEM: Probability of discharge at given gain lower by more than one order of magnitude compared to DGEM

Sectorized foils: Decrease energy stored in GEM foils

- Charge released in a GEM discharge smaller
- Probability of propagating discharge lower

"Beam killer": Central area of $5 \text{ cm } \phi$ can be deactivated

Readout: 2-dim, 2×768 strips, $400 \mu\text{m}$ pitch

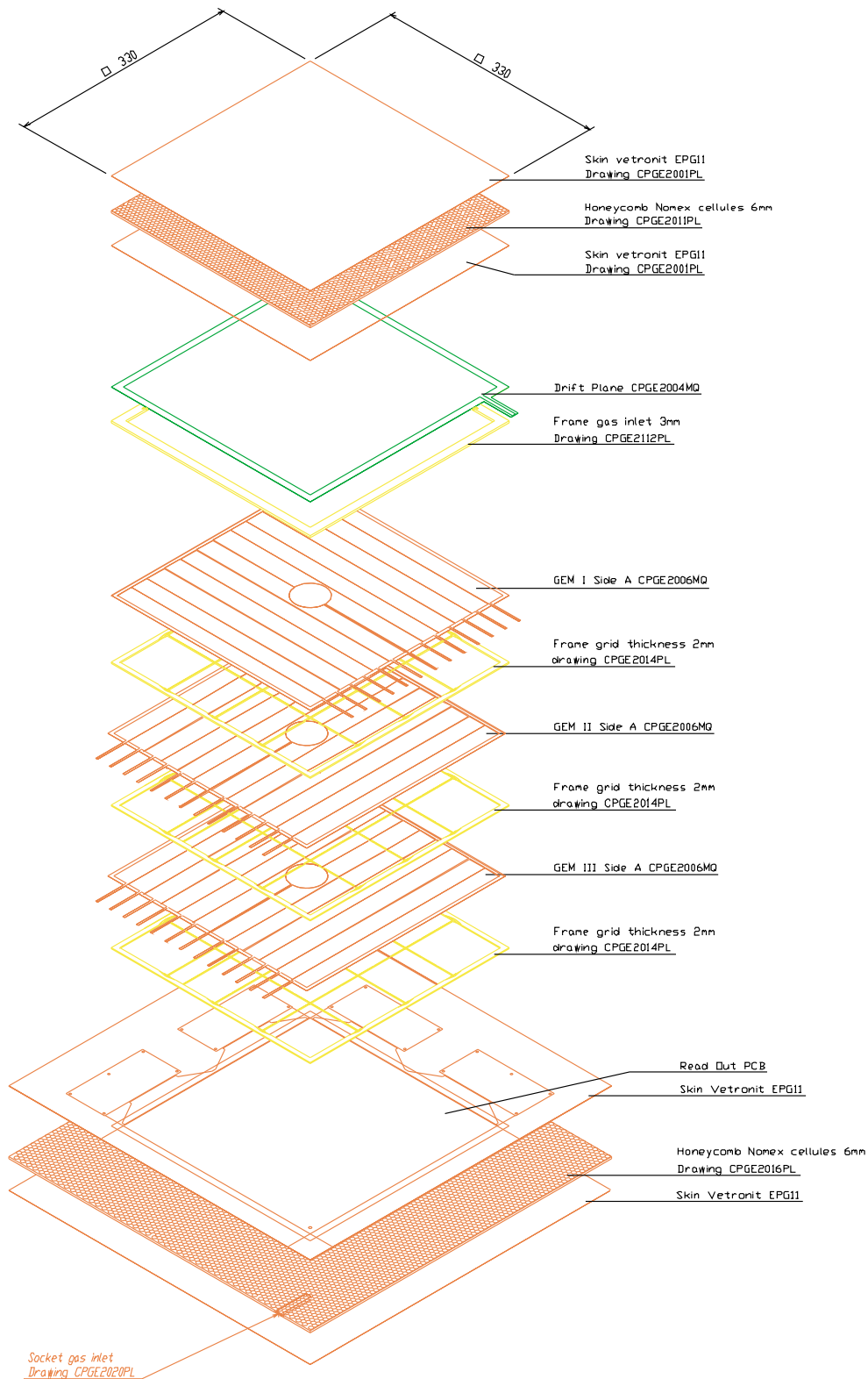
⇒ Active area $30.7 \times 30.7 \text{ cm}^2$

Thickness of detector: 15 mm

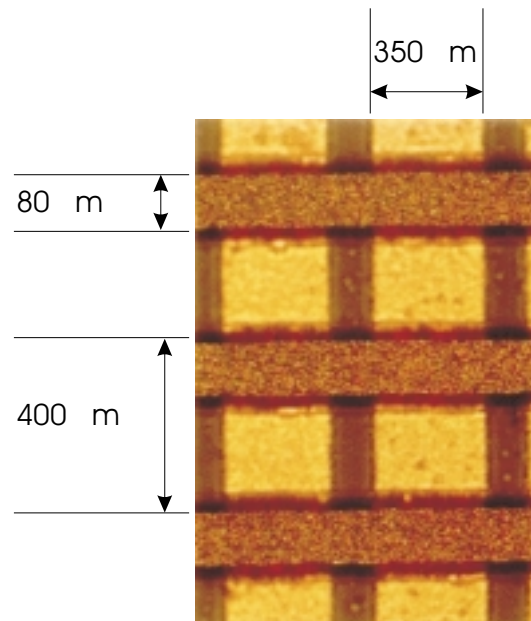


COMPASS GEM design II

AXONOMETRIC EXPLODED VIEW



Two-dimensional Readout



Production process [A. Gandi, R. de Oliveira, CERN-EST]

- Two orthogonal sets of parallel Cu strips, engraved on two sides of Cu-clad Kapton foil ($50\ \mu\text{m}$ thin):
 - $80\ \mu\text{m}$ width on upper side
 - $350\ \mu\text{m}$ width on lower side
 - $400\ \mu\text{m}$ pitch
- Gluing of Kapton foil onto a thin insulating support (fiber glass)
- Chemical removal of Kapton in the interstices between the strips on the upper side
 - ⇒ Bottom layer of strips is opened to charge collection
- Charge sharing 1 : 1 between upper and lower layer achieved by adjusting strip widths

Construction of GEM detectors



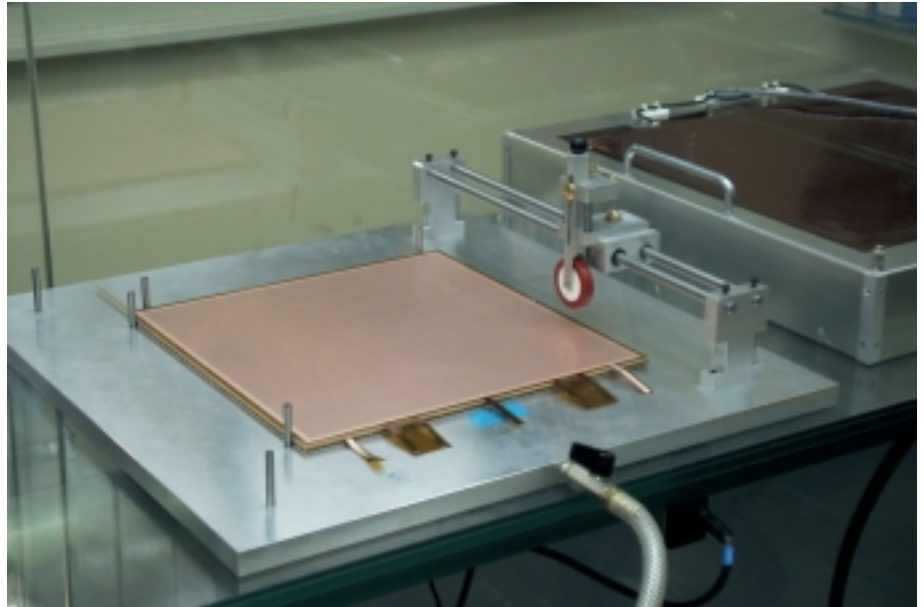
- Carried out by K. Dehmelt [Univ. Mainz] and M. van Steenis [CERN-EP/TA1] in TA1 cleanroom: class < 10000 , humidity + temperature controlled
- Protective clothing: overall, shoe-covers, hair-covers, facial masks, gloves



Construction – Tools & Materials

Tools: designed by M. Delattre and M. van Stenis

- Alignment plate and gluing tool
- Heating cover with N₂ flow
- HV test box with N₂ flow



Materials:

Glue:	ARALDIT AY103 + HD991 (ratio 10:4)
Support:	2 × 125 μm Stesalit on 3 mm Honeycomb Nomex
Drift foil:	5 μm Cu on 50 μm Kapton
GEM foils:	2 × 5 μm Cu on 50 μm Kapton
Frame:	3 mm Stesalit
Spacer grid:	2 mm Vetronite
Sealant:	Polyurethane Nuvoern LW (2 comp.)
Strip PCB:	2 × 5 μm Cu on 50 μm Kapton, 60 μm NoFlow glue, 120 μm Stesalit
Shielding	5 μm Aluminum



Triple GEM Material Budget

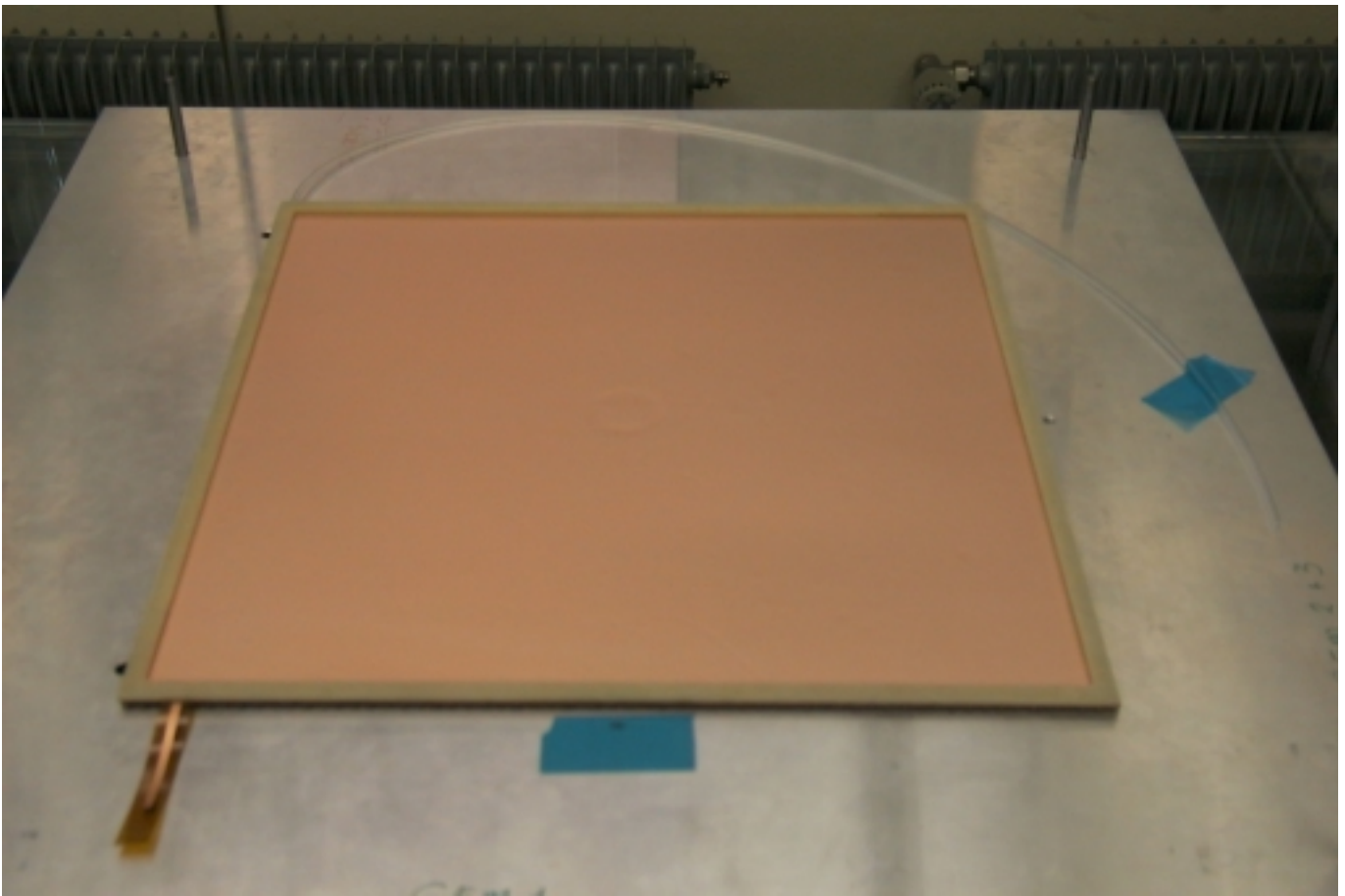
Part	Material	$^0/_{00}$ of X_0
GEM	Cu: $6 \times 5 \mu\text{m}$ ($X_0 = 14.3 \text{ mm}$) $\times 0.8$	1.68
	Kapton: $3 \times 50 \mu\text{m}$ ($X_0 = 286 \text{ mm}$) $\times 0.8$	0.42
		Total: 2.1
Drift	Cu: $5 \mu\text{m}$	0.35
	Kapton: $50 \mu\text{m}$	0.17
		Total: 0.52
Grid	G10: $3 \times 2 \text{ mm}$ ($X_0 = 194 \text{ mm}$) $\times 0.008$	Total: 0.25
PCB	Cu (80 μm strips): $5 \mu\text{m} \times 0.2$	0.07
	Cu (350 μm strips): $5 \mu\text{m} \times 0.75$	0.26
	Kapton: $50 \mu\text{m} \times 0.2$	0.03
	G10: $120 \mu\text{m}$	0.62
	NoFlow Glue: $60 \mu\text{m}$ ($X_0 = 200 \text{ mm}$)	0.30
	Total: 1.28	
Shield	Al: $5 \mu\text{m}$ ($X_0 = 89 \text{ mm}$)	Total: 0.06
		Total: 4.21
HC	NOMEX: $2 \times 3 \text{ mm}$ ($X_0 = 13125 \text{ mm}$)	Total: 0.46
Skins	G10: $4 \times 120 \mu\text{m}$	Total: 2.47
		Total: 7.14



Construction Steps I

Assembly starts from drift side:

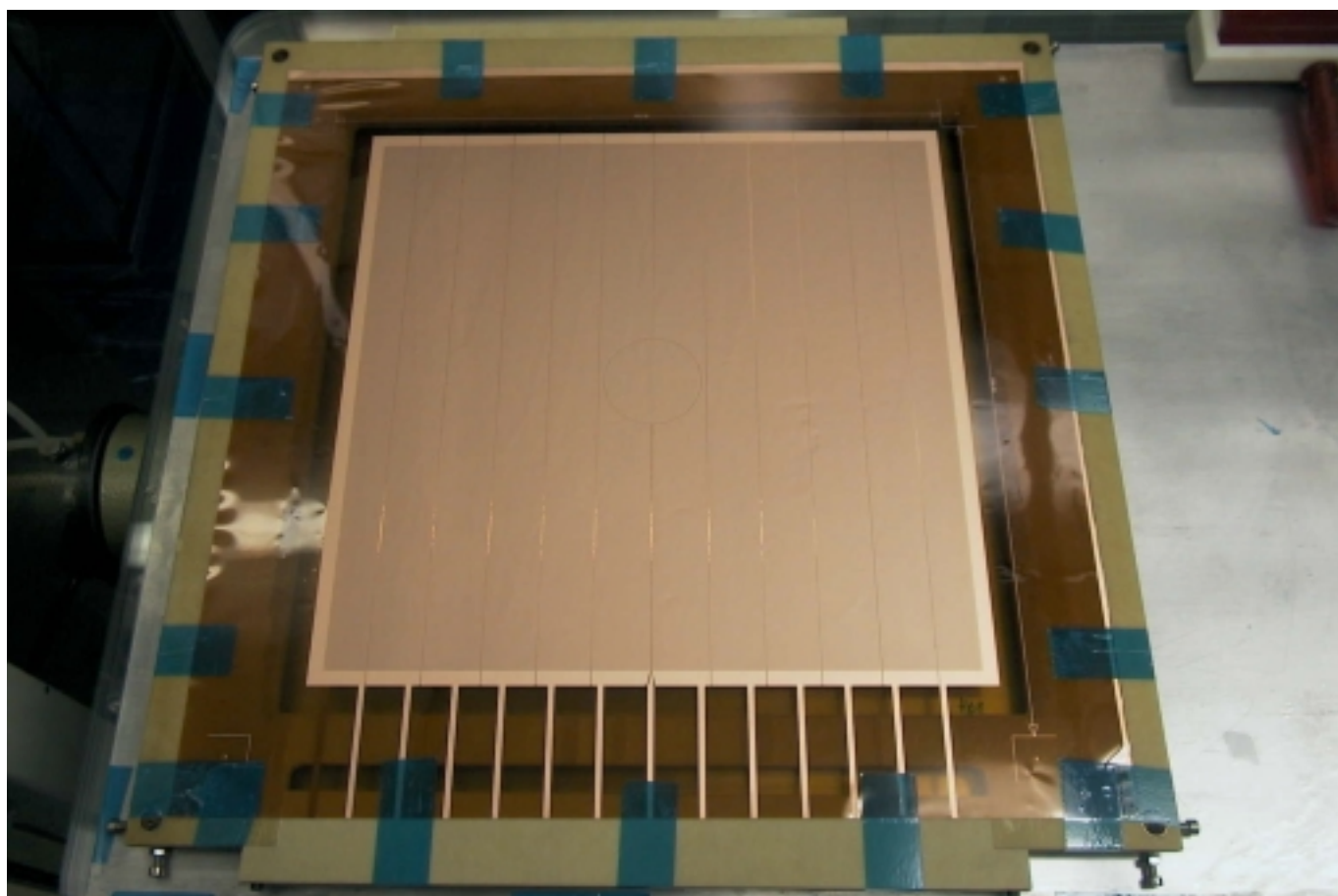
- Glue Stesalit skins onto honeycomb ($330 \times 330 \text{ cm}^2$)
- Glue drift foil onto honeycomb sandwich
- 3 mm frame with gas distribution channels
 - Seal with Polyurethane
 - Clean in ultrasonic bath
 - Test for HV stability (up to 5 kV)
 - Glue gas input pipe
- Glue frame onto drift foil



Construction Steps II

Pre-tension GEM foil

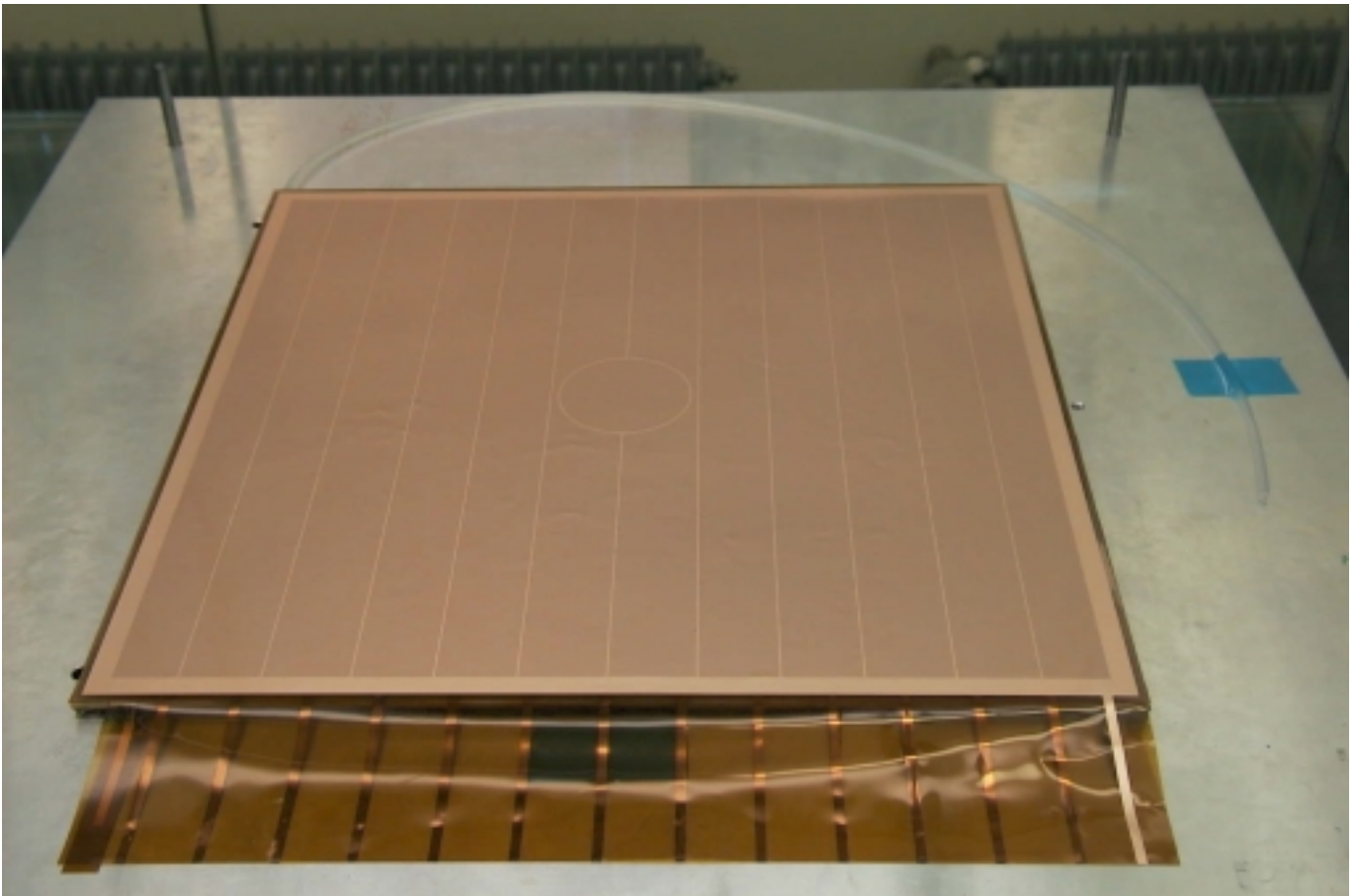
- Stretch GEM foil over transfer frame
- Glue GEM foil onto transfer frame
- HV test



Construction Steps III

Glue GEM foil

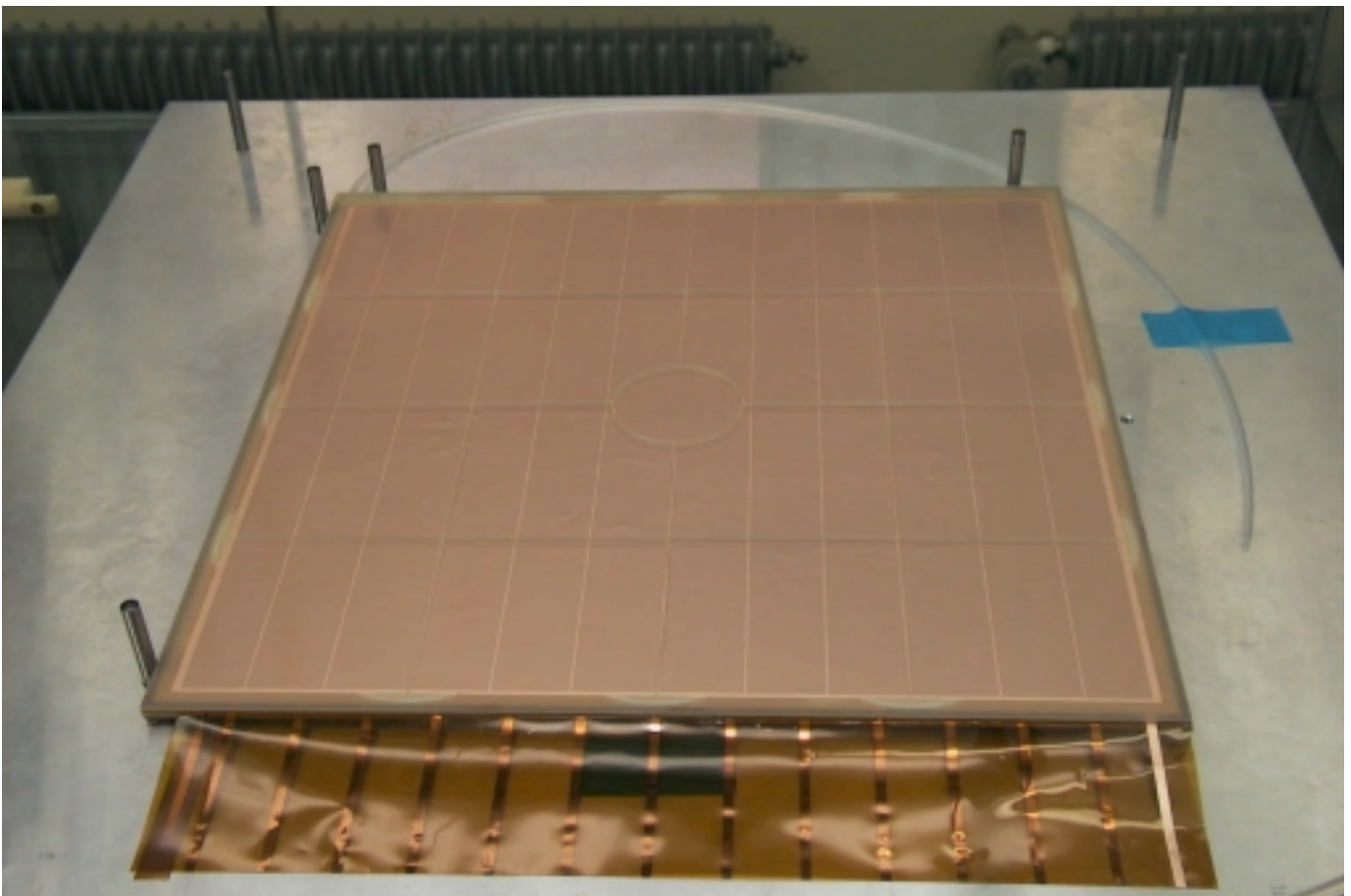
- Mount drift honeycomb on alignment plate, fix with vacuum
- Apply glue to the frame using gluing wheel
- Align GEM on transfer frame to honeycomb using pins
- Apply weight to the transfer frame to stretch GEM
- Cut out GEM from transfer frame
- HV test



Construction Steps IV

Glue spacer grid

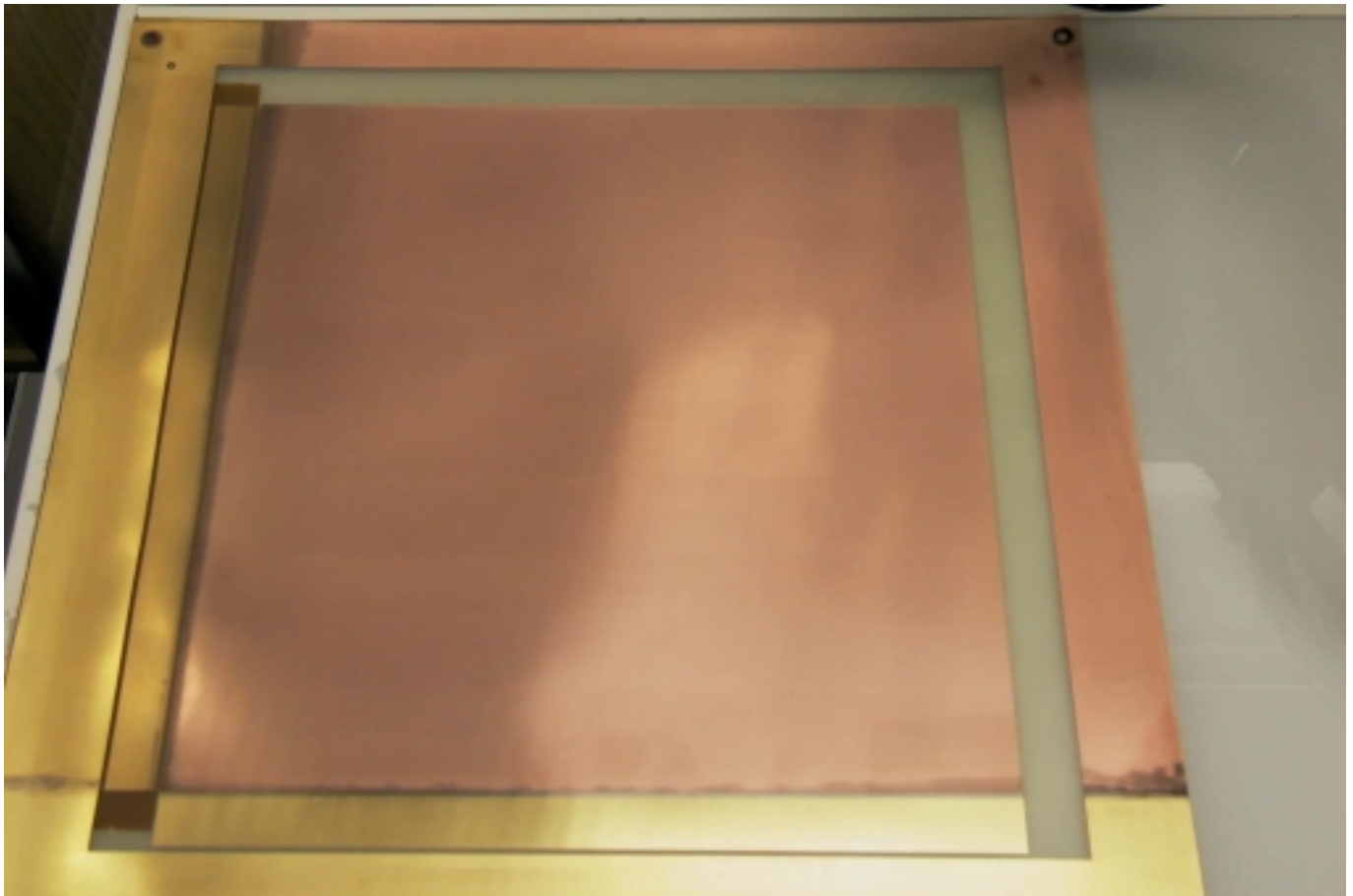
- Apply glue to the spacer grid using gluing wheel
- Mount drift honeycomb on alignment plate, fix with vacuum
- Align spacer grid to honeycomb using pins
- Apply weight to the spacer grid
- HV test



Construction Steps V

Large honeycomb, Strip PCB

- Insert gas outlet piece into honeycomb
- Glue Stesalit skins onto honeycomb ($500 \times 500 \text{ cm}^2$)
- Strip PCB:
 - Measure strip pitch and deviation from parallelism
 - Check for shorts

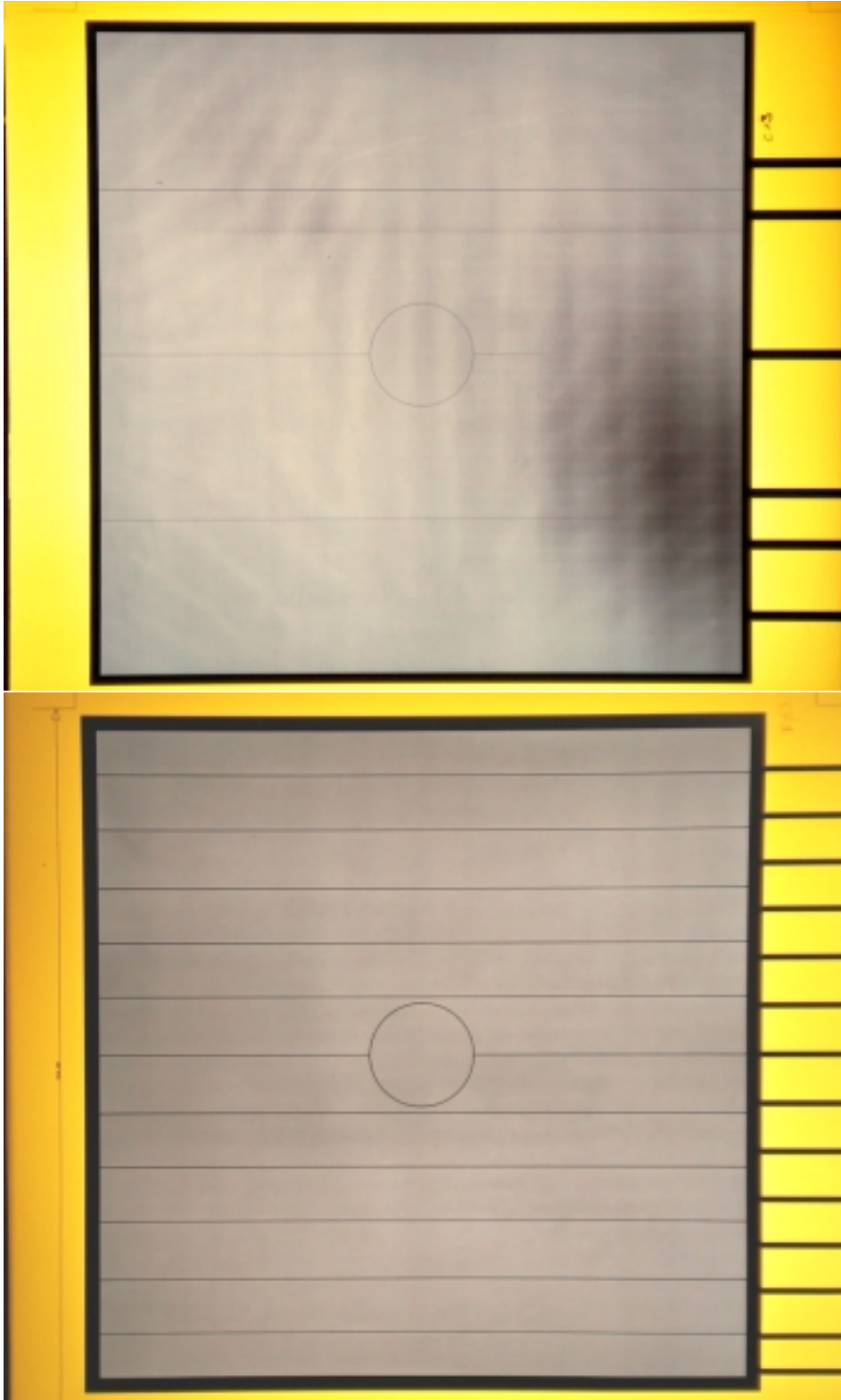


- Glue strip PCB onto honeycomb sandwich
- Close detector by gluing drift stack onto large honeycomb using alignment pins inserted into large honeycomb

GEM quality control I

Optical transparency

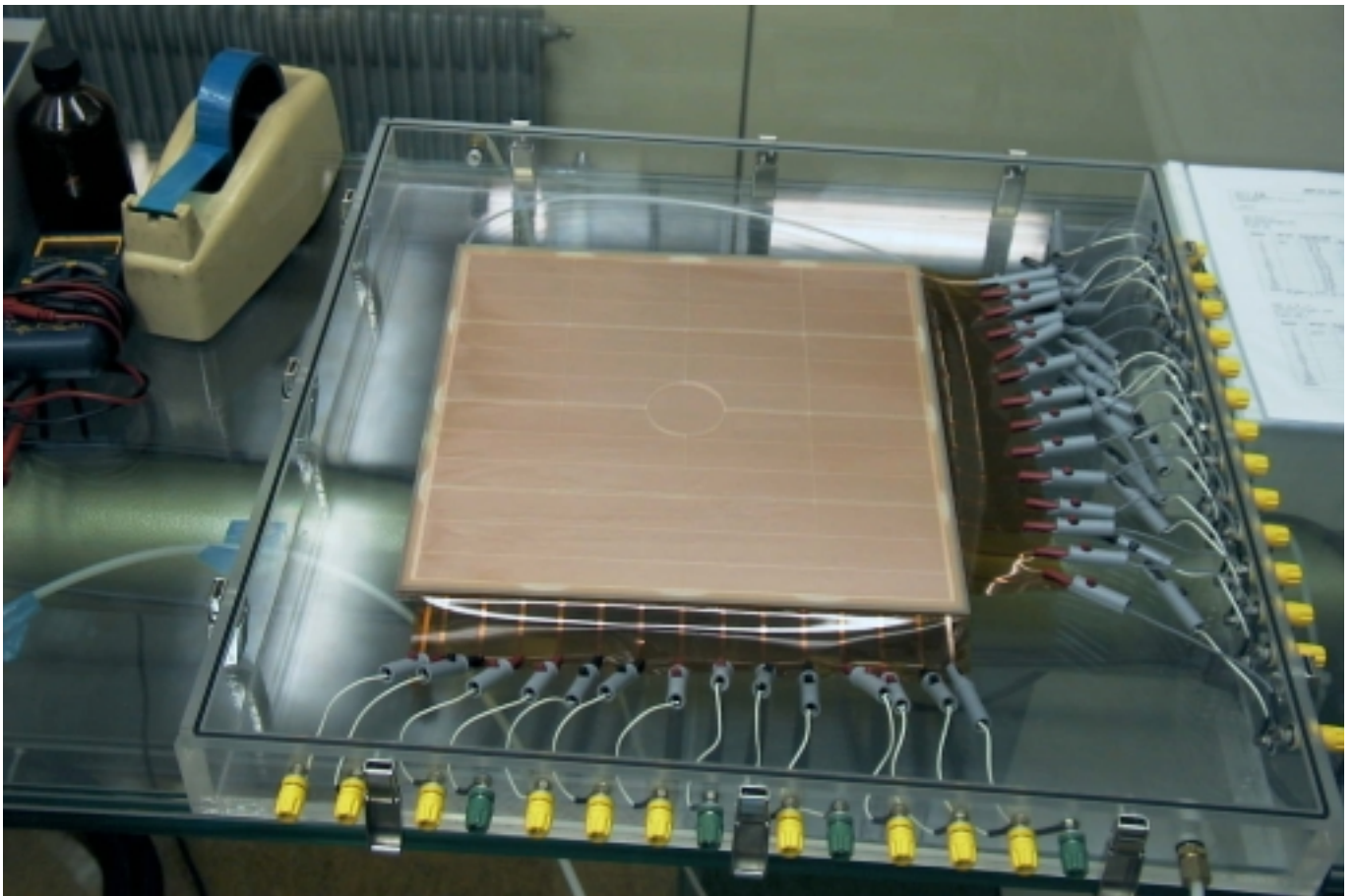
⇒ relative alignment of holes in two Cu electrodes



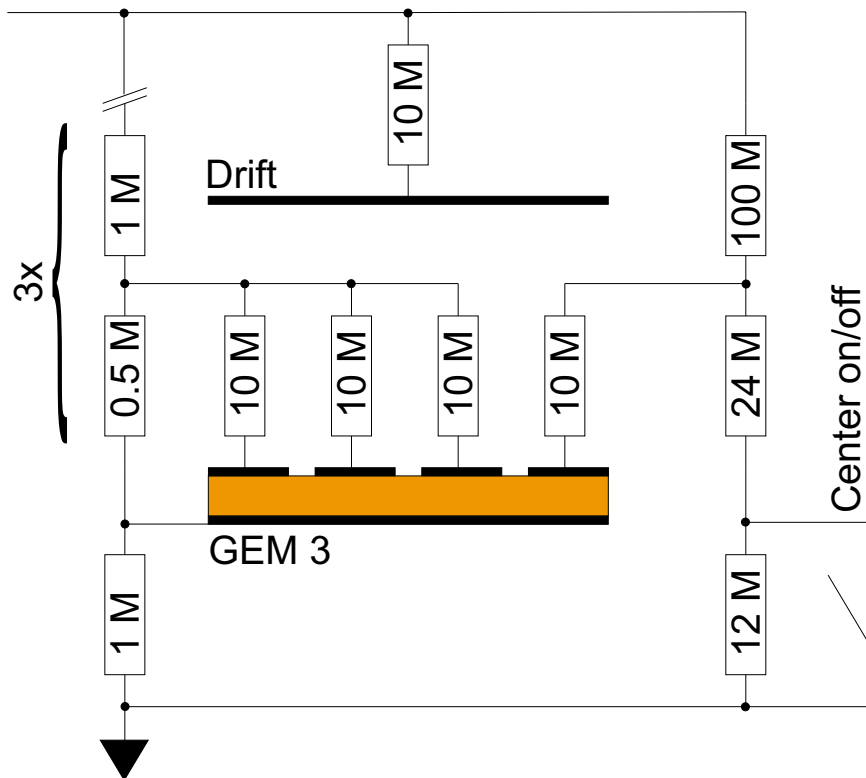
GEM quality control II

HV test:

- up to 600 V before mounting
 - up to 550 V after each gluing step
- ⇒ monitor leakage currents of sectors, shorts



HV Distribution



- **Resistor network** instead of individual power supplies
- Main chain defines fields between foils and gain in GEM
- **Individual protection resistors** on upper GEM side: $10 \text{ M}\Omega$
⇒ Most of the potential drop on upper side in case of discharge! Limitation: max. 5 V potential drop under exposure to high intensity beam (10^8 s^{-1} , $G = 5 \cdot 10^3$)
- **Operational even with permanent short** in one sector: small drop of potential in remaining sectors can be compensated by slightly increased HV
- Room for improvement: sectorization on both sides of the GEM foils

Detector Quality Control

Gas leak test (pure CO₂)

HV distribution boards:

- Chemical cleaning of boards after assembly of resistors
- Coating of boards with HV-proof varnish
- Test of each individual board before mounting

HV stability:

- Test of each individual GEM foil before mounting HV boards (pure CO₂)
- Test for external discharges at nominal voltage (pure CO₂)
- Test for internal discharges at nominal voltage (Ar/CO₂)

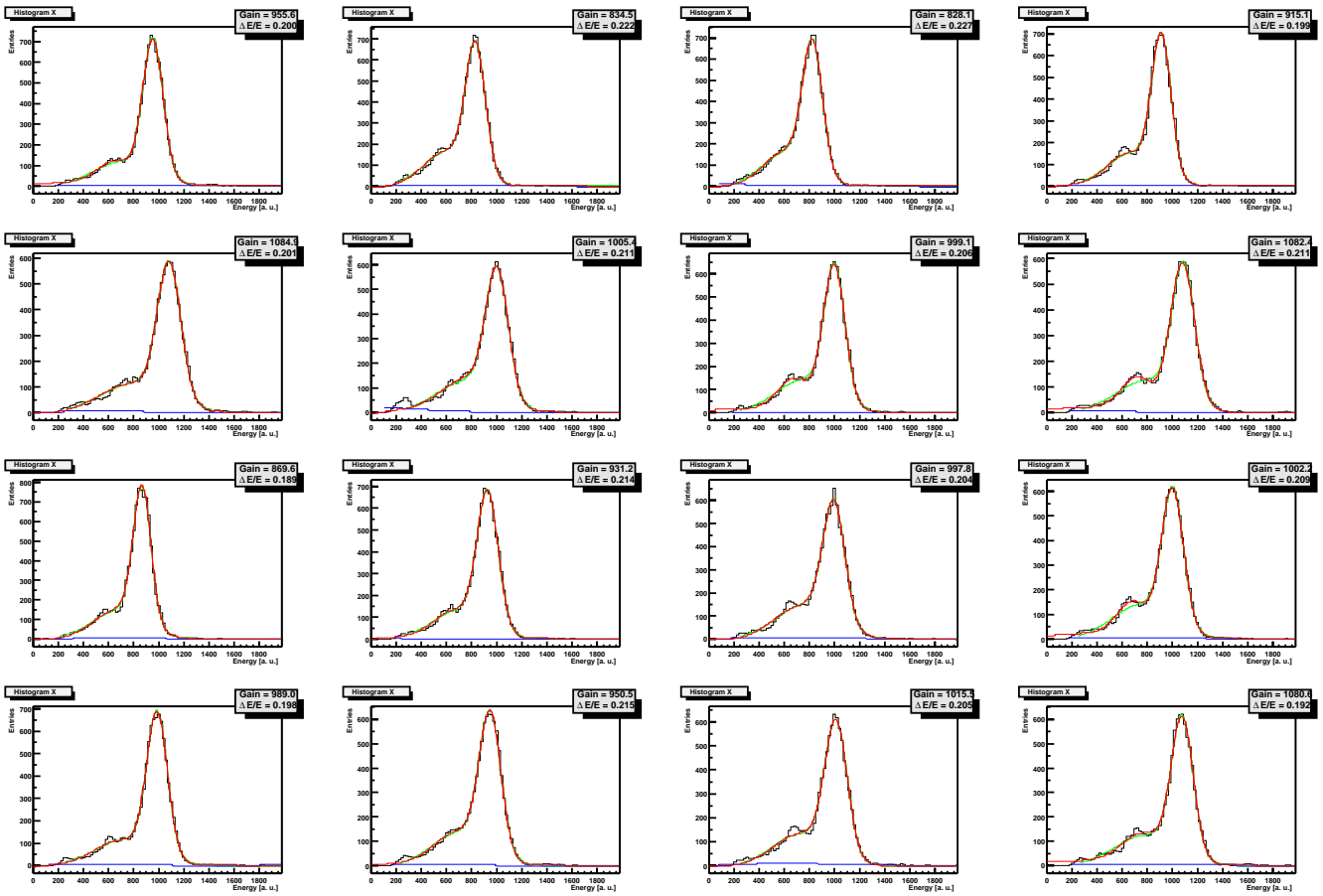
Detector performance:

- Check for shorts in readout circuit
- Gain map with 8.9 keV X-rays, using standard laboratory preamplifier/amplifier

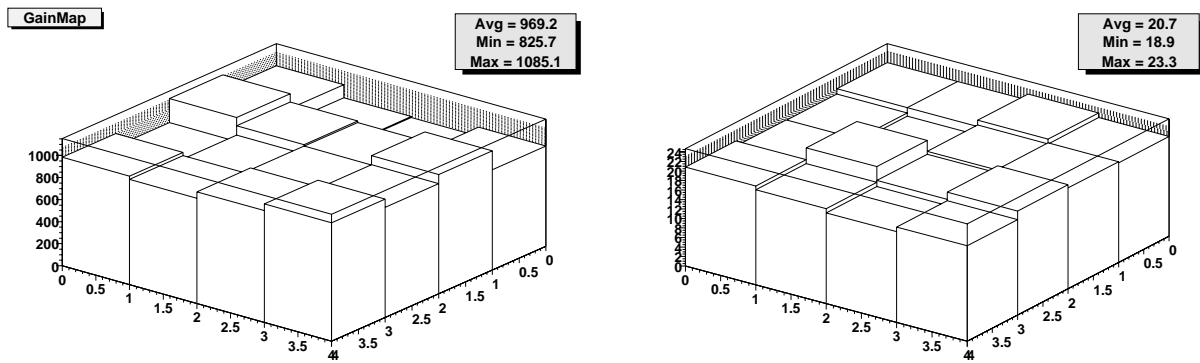


Uniformity of Gain and Resolution

Cu X-ray spectra (8.9 keV) in 4×4 points over each detector for both strip layers



Maps of relative gain and energy resolution

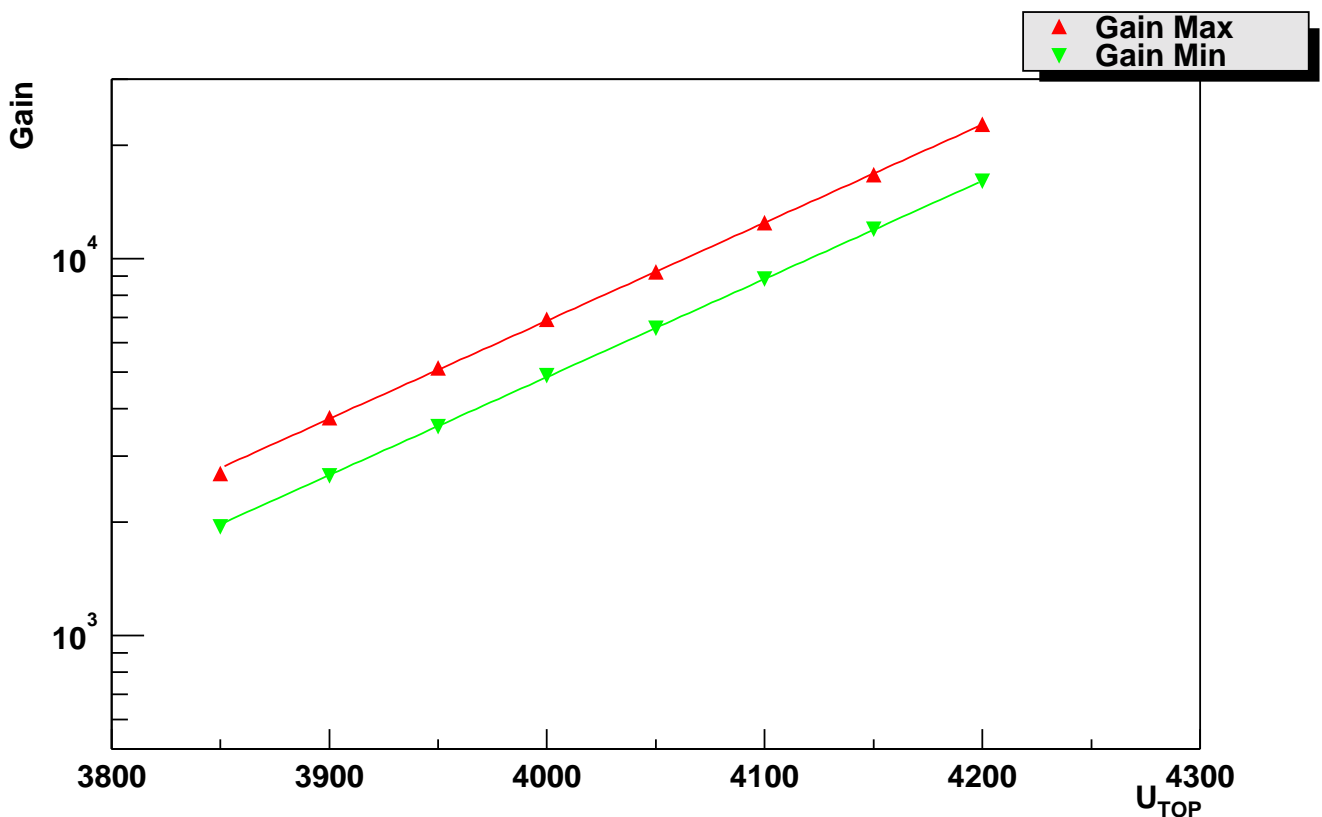


Gain Calibration

Effective gain: measure current on readout strips I as a function of count rate R under irradiation with 8.9 keV X-rays

$$G = \frac{I}{e_0 N R}, \quad e_0 N : \text{primary charge}$$

Gain calibration at points with maximum and minimum gain



TGEM11



COMPASS GEM

Bernhard Ketzer

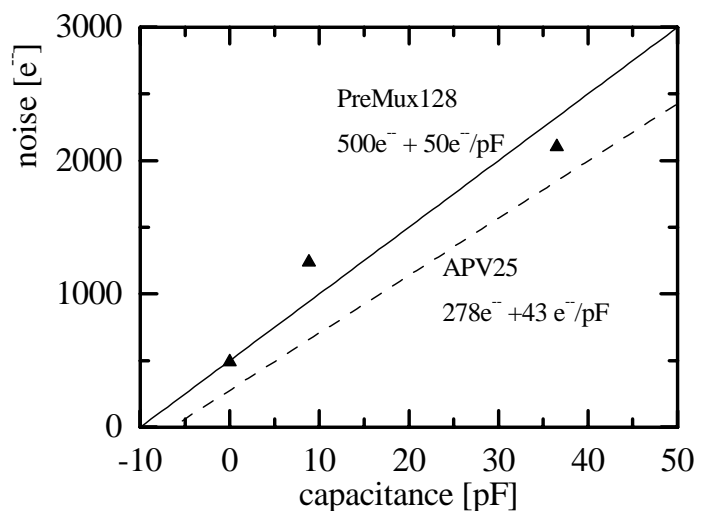
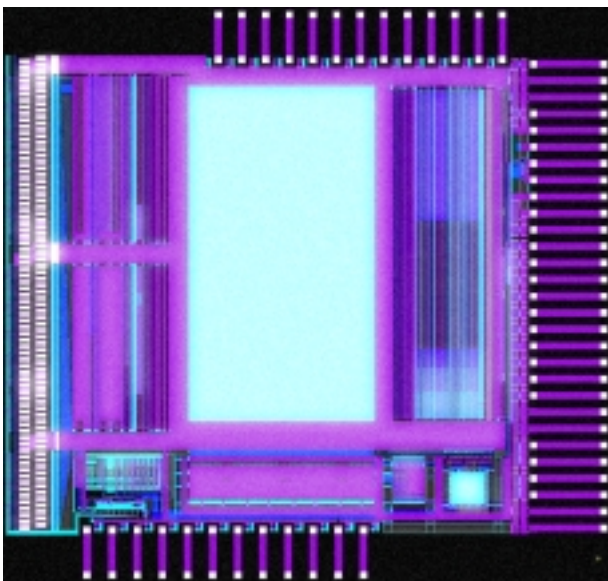
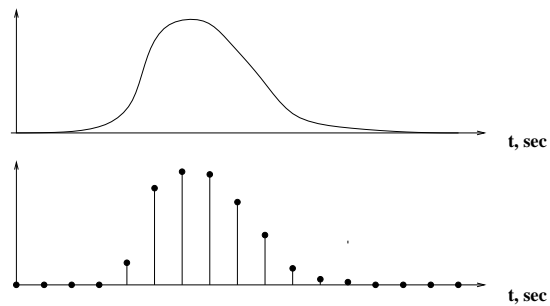
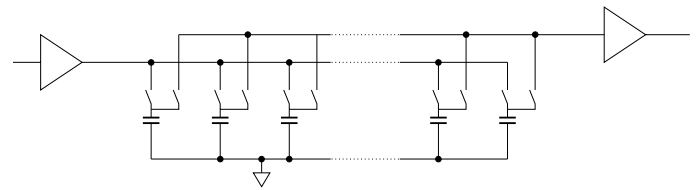


GEM Readout

"Deadtime-less" frontend electronics \Rightarrow Pipeline

APV25-S0: CMS Si microstrip tracker FE chip

- Analogue pipeline ASIC fabricated in $0.25\ \mu\text{m}$ CMOS technology
- Preamplifier + shaper (50 ns peaking time)
- 192 memory cells / channel
- Samples written at 40 MHz
- FIFO depth 31 events \Rightarrow Latency up to $4\ \mu\text{s}$
- MUX output

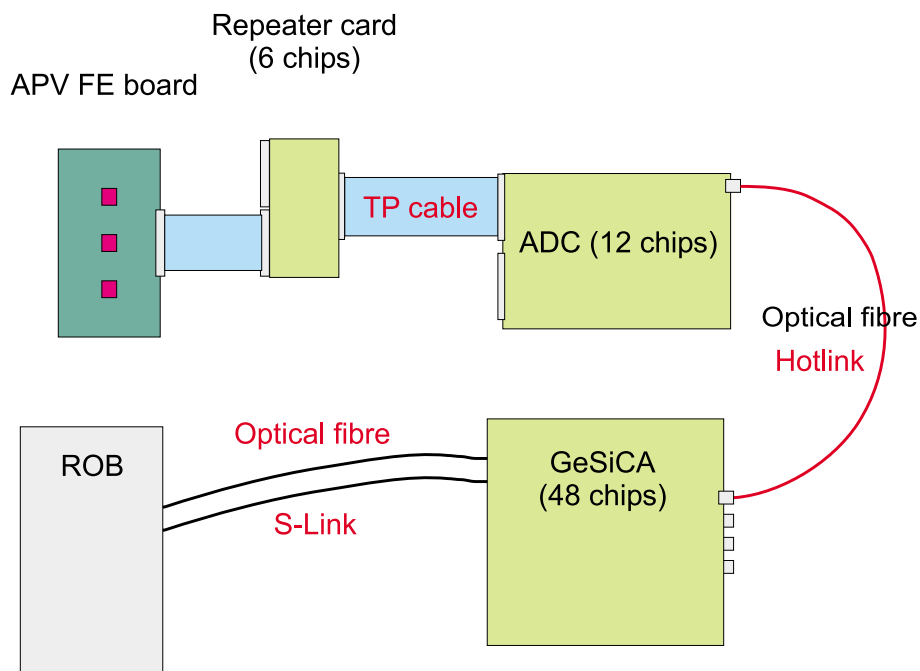


Front-end Electronics

FE-card: 3 APV chips, glass pitch adapter, 220 pF capacitors, BAV99 double diodes for input protection



Readout chain: designed and built by I. Konorov (TU München)



COMPASS SAT – Beam Tests

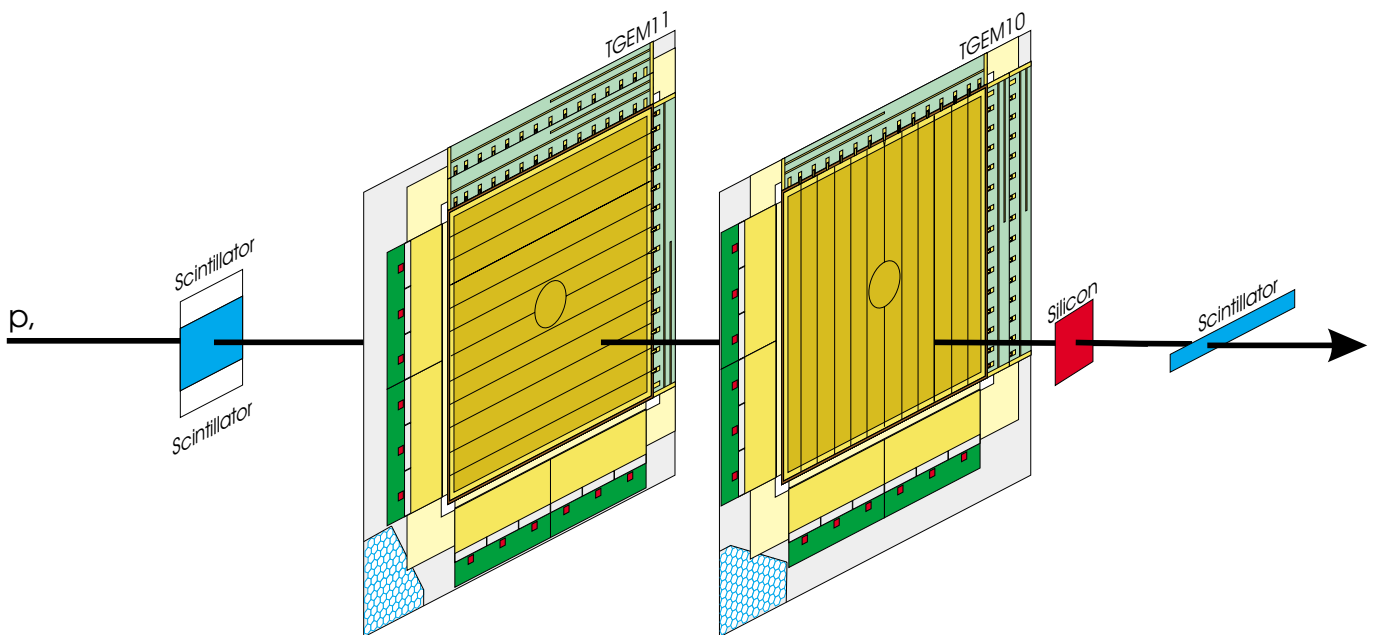
CERN PS-T11: $10^6 p, \pi/\text{spill}$, $3.6 \text{ GeV}/c$

3 triple GEM detectors:

- 2 fully equipped with electronics (3072 channels)
- 1 half equipped with electronics (768 channels)

1 Si microstrip detector:

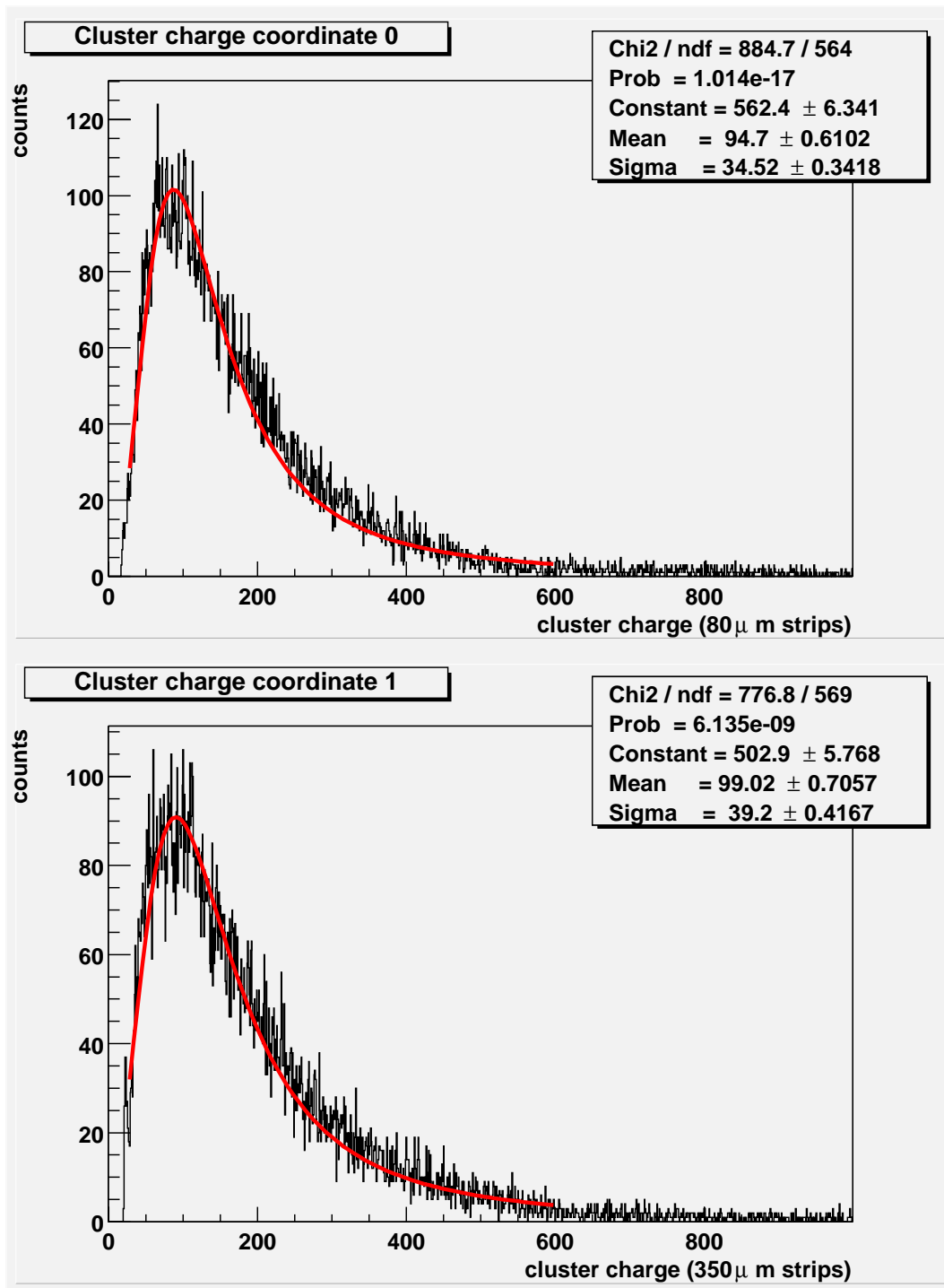
- $5 \times 7 \text{ cm}^2$, double-sided, $300 \mu\text{m}$ thick
- $50 \mu\text{m}$ strip pitch (2304 channels)



Cluster Amplitudes

Single cluster, $U_0 = 4050 \text{ V}$ ($G \sim 8000$)

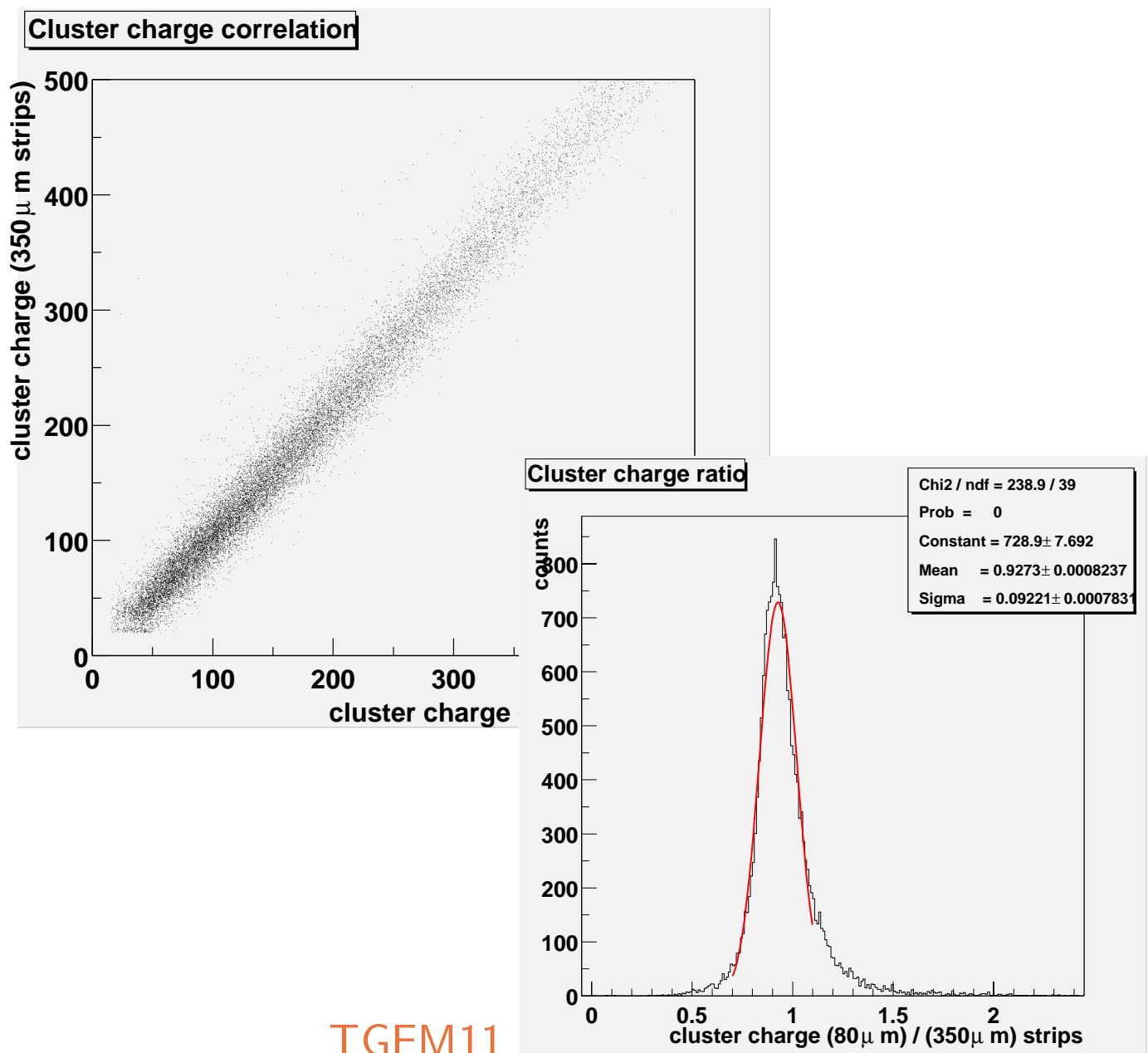
TGEM11



- Strip noise: $1050 e^-$ ($80 \mu\text{m}$), $1250 e^-$ ($350 \mu\text{m}$)



Cluster Amplitude Correlation

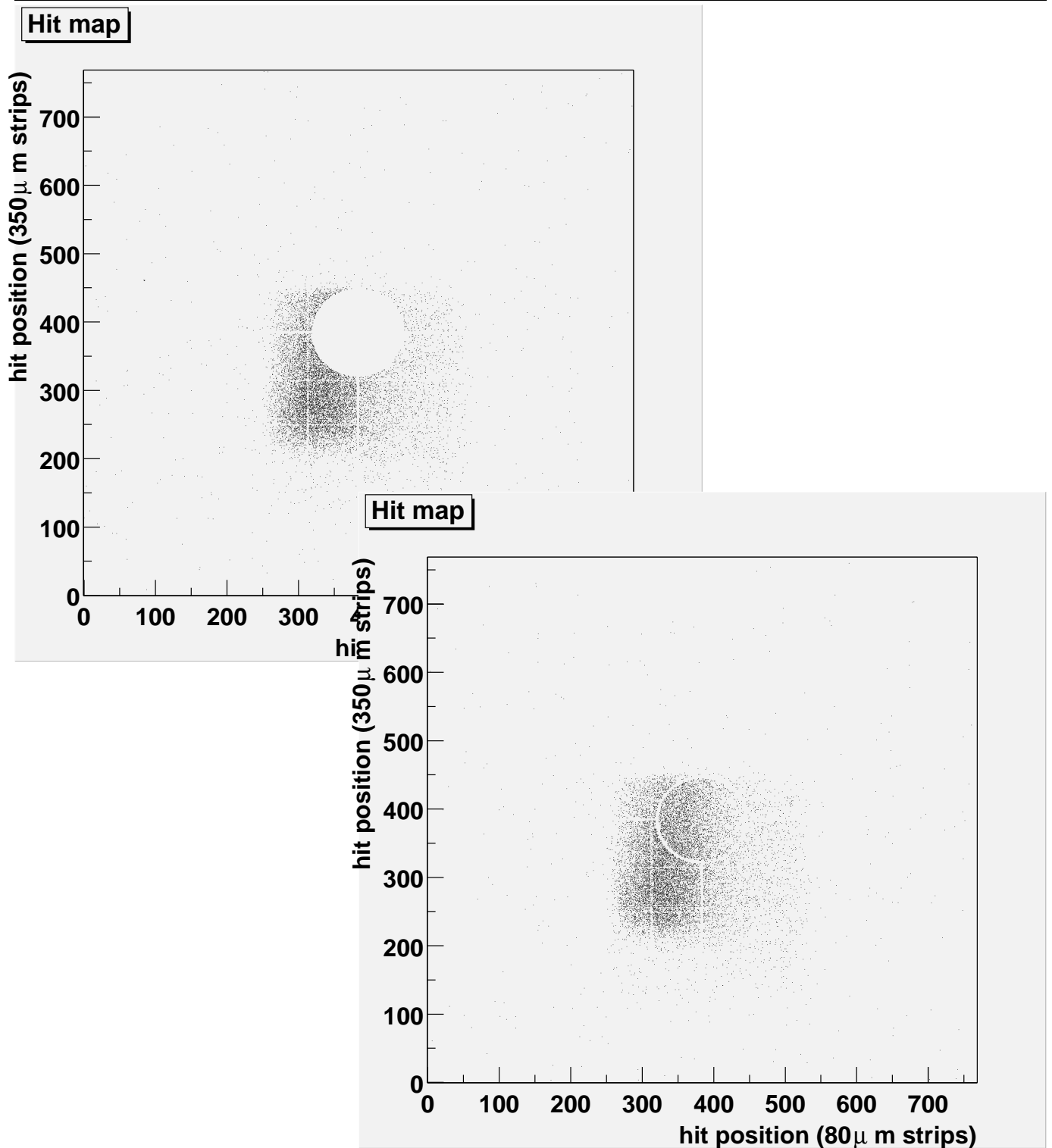


- Charge sharing between strip planes ~ 1
- Narrow correlation between amplitudes: $\sigma = 0.09$

\Rightarrow Resolve hit ambiguities



Hit Map



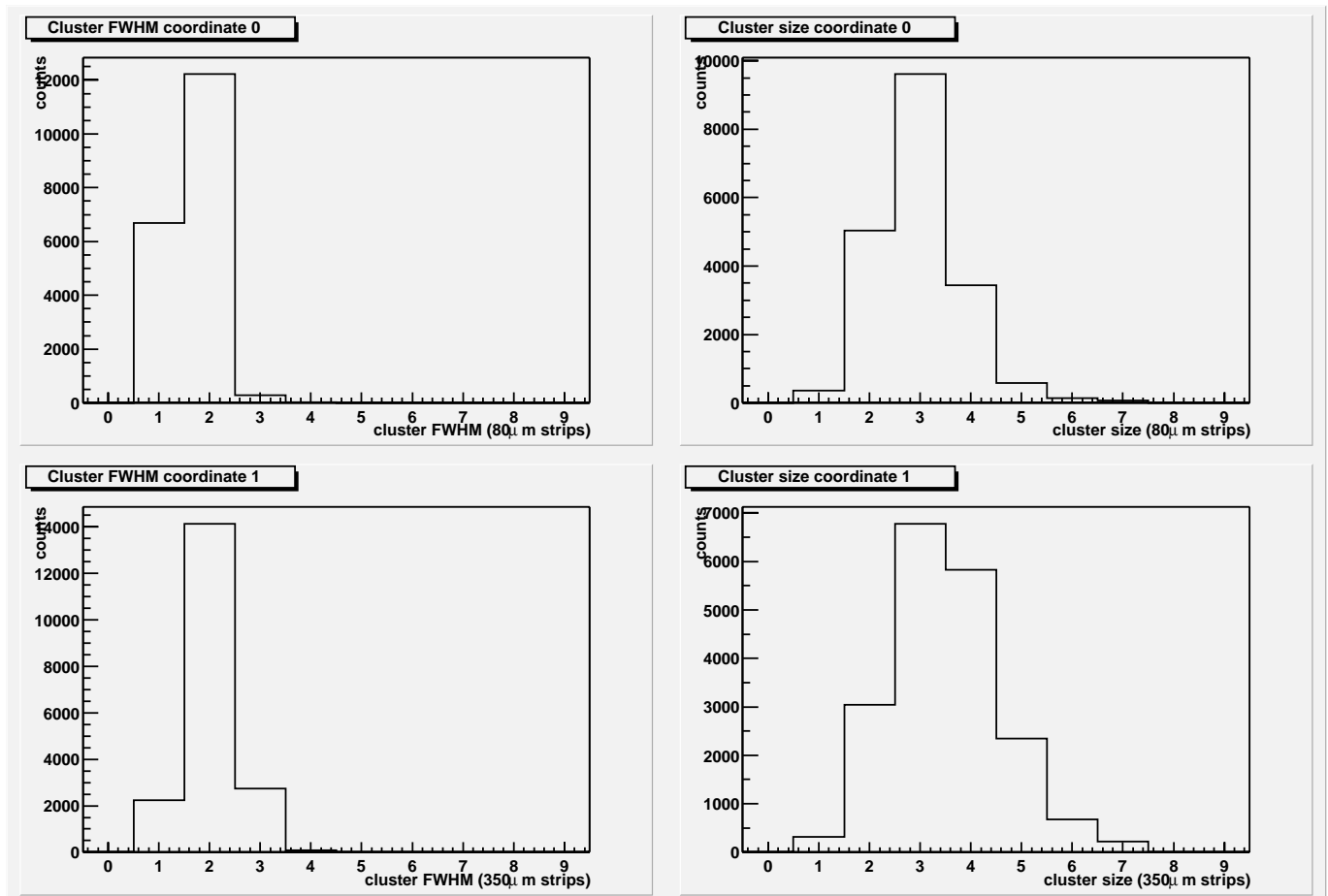
- Image of scintillator used for triggering clearly visible
- Deactivation of central part works efficiently
- Inactive regions underneath spacer grid



Cluster Size

Cluster:

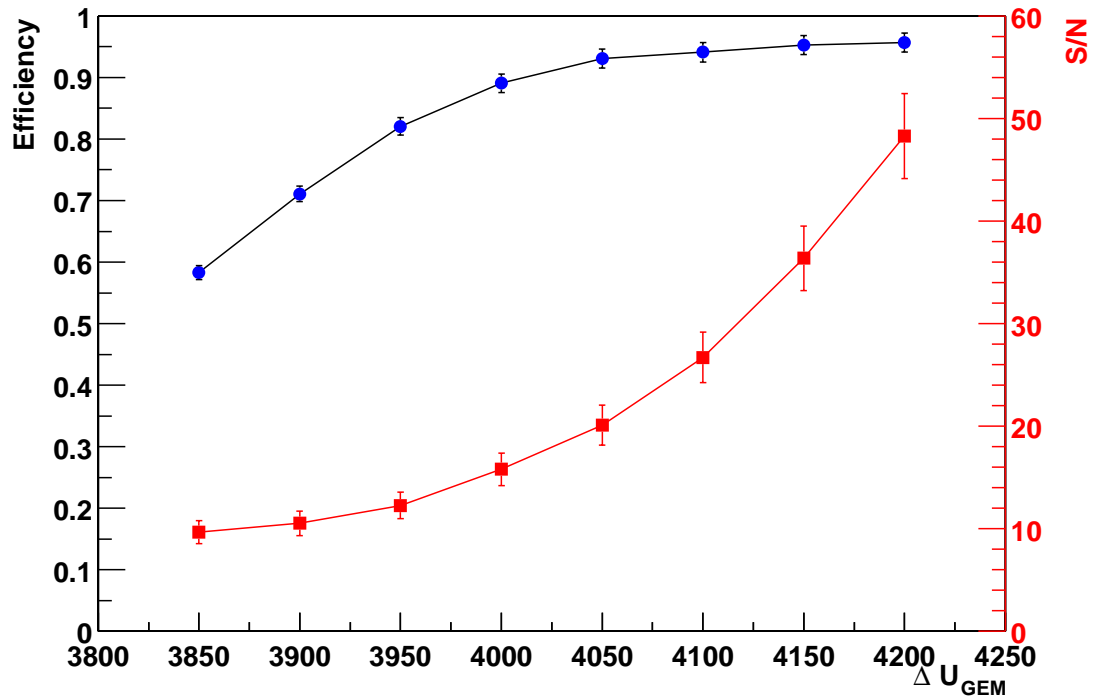
- strip amplitude $> 3\sigma_i$
- cluster amplitude $> 5\sqrt{\sum_i \sigma_i^2}$



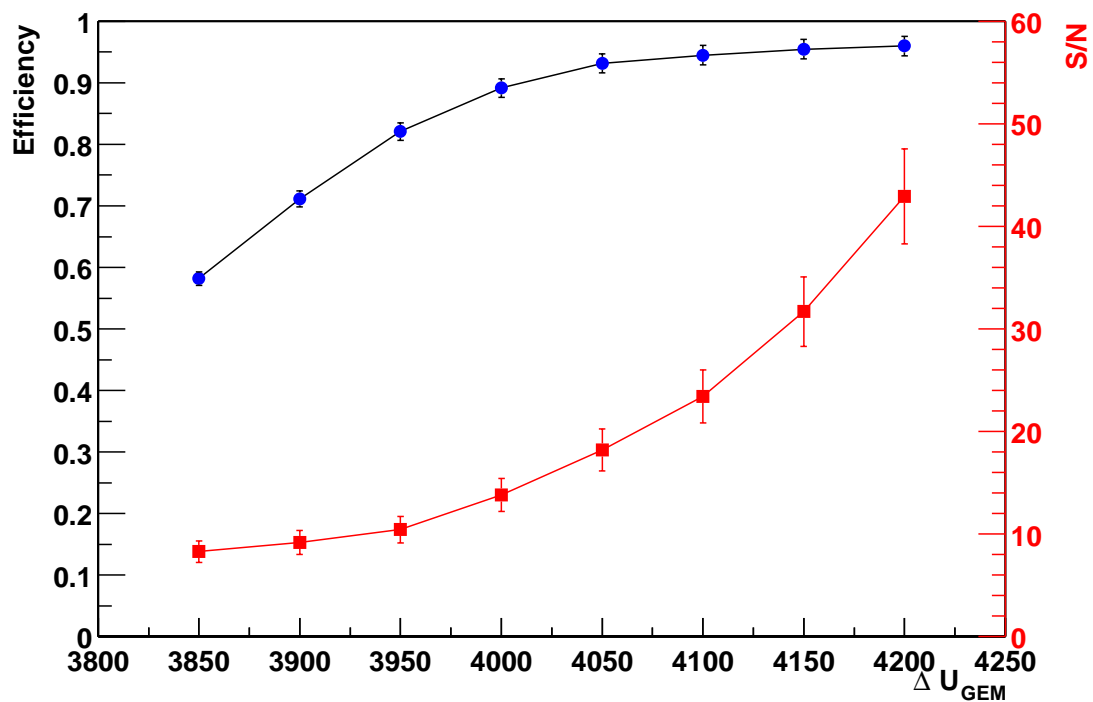
Efficiency

80 μm strip layer:

TGEM11

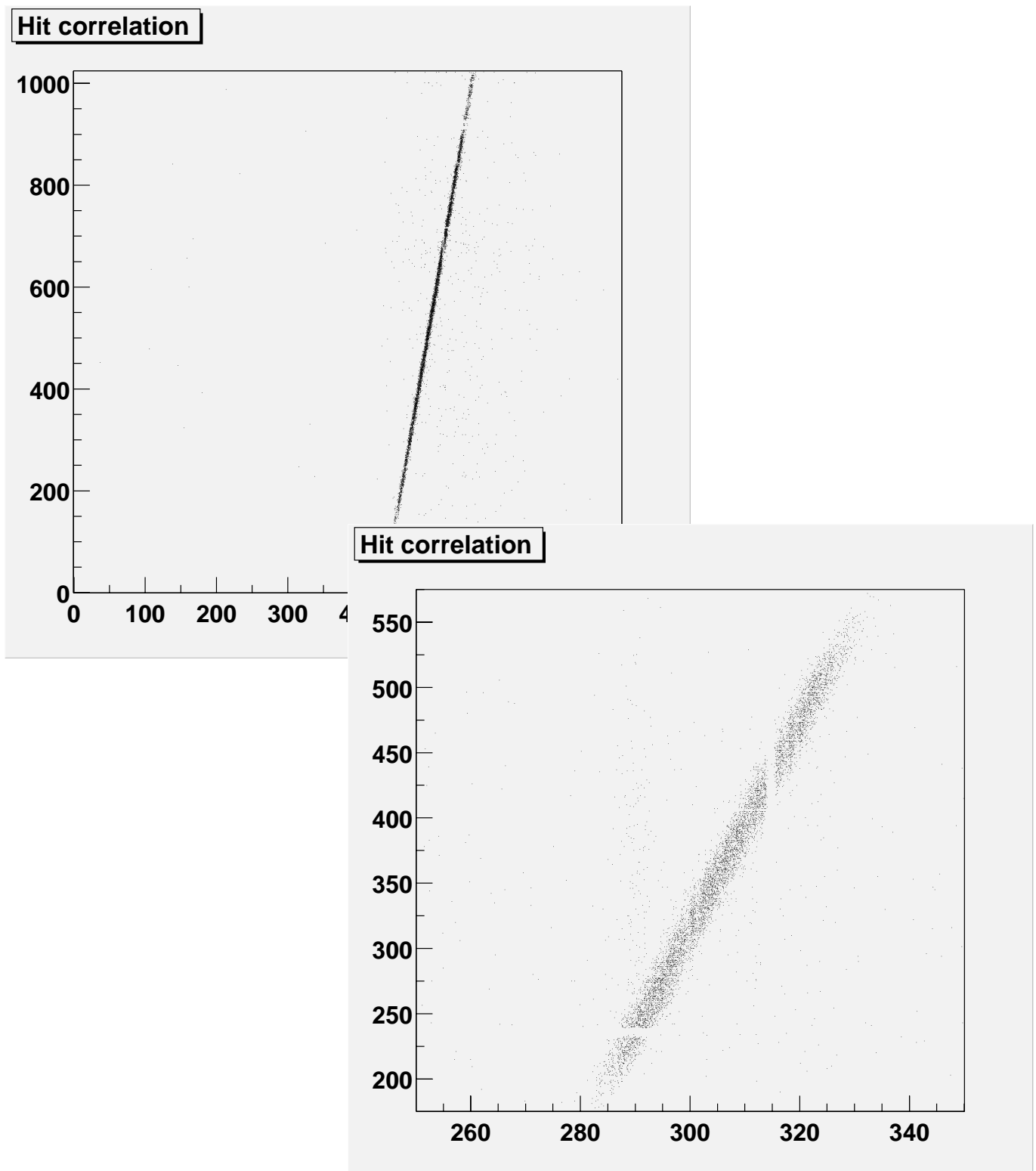


350 μm strip layer:



Hit Correlations

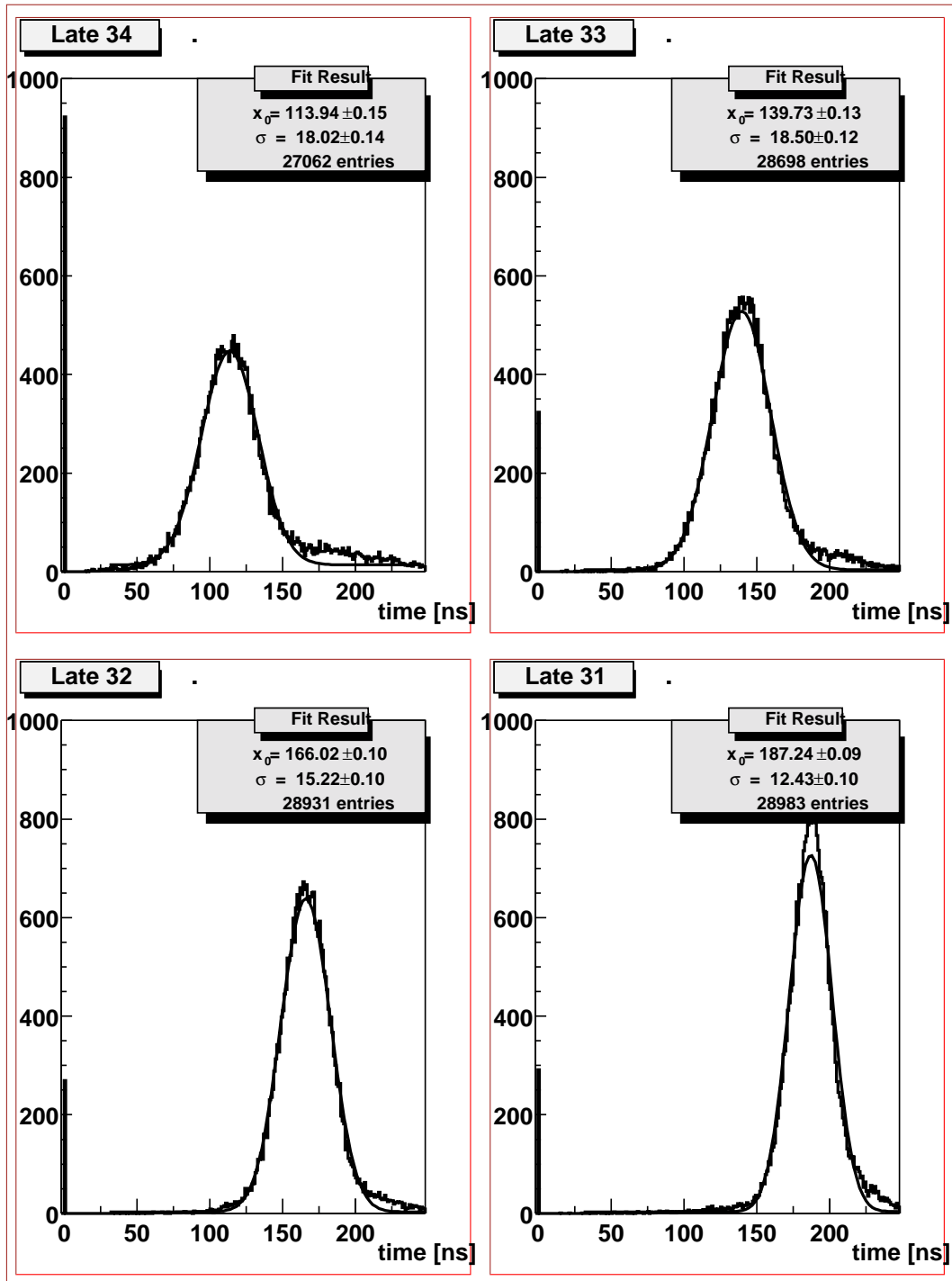
TGEM11 — SIL6, two projections



Time Resolution

APV25: 3-sample readout, rising edge of signal

Timing TGEM10 pr01 (Biggest Cluster)



Summary

GEM detectors meet requirements for tracking devices in modern HEP experiments:

- high rate capability
- no aging observed
- large active area
- thin, little material
- cheap

COMPASS adopted GEM detectors for SAT:

- $31 \times 31 \text{ cm}^2$ active area
- 2-dimensional projective readout

Optimization

- triple GEM amplification
- sectorization of GEM foils
- asymmetric gain sharing
- input protection for FE chip APV25 S0

Beam test of COMPASS GEM detectors

- no loss of electronic channels
- low noise
- efficiency plateau reached at gain ~ 8000 , $S/N \sim 18$
- narrow correlation of pulse heights
- time resolution $< 15 \text{ ns}$



Outlook

Production of GEM detectors for COMPASS

- Ongoing at CERN-EP/TA1
- 9 detectors of final design assembled
- test procedures for QC of components and detectors defined

Goal for 2001: **14 detectors** (70 % of total)

The Group

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